

能源革命的驱动力-碳化硅引领未来

宽禁带半导体-安森美碳化硅方案

2024-04-09

熊壮

WPI-PMO华南技术支援组

Agenda

- 半导体发展历程;
- 宽禁带半导体概述;
- SiC MOSFET应用设计经验分享;
 - SiC MOSFET针对不同拓扑和开关模式的关键参数;
 - SiC MOSFET分立器件并联时均流风险与解决方案;
 - 平面栅工艺SiC MOSFET驱动做0V关断电压可行性;



半导体材料发展历程

第一代/第二代/第三代半导体材料及主要应用

参考资料:

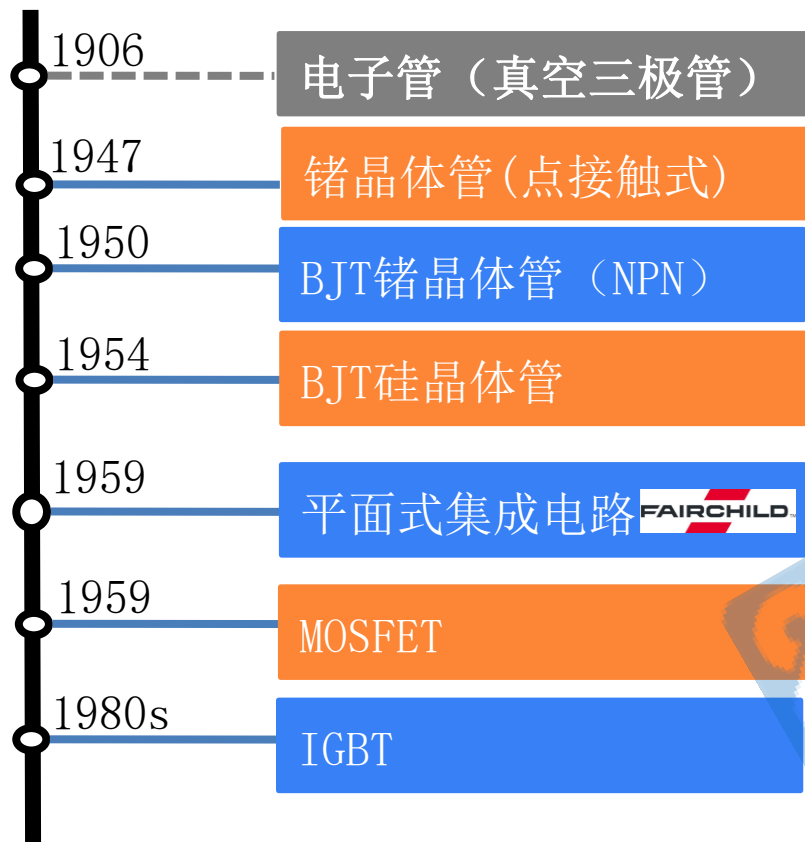
<https://www.onsemi.com/download/application-notes/pdf/and90103-d.pdf>

DOI: 10.19772/j.cnki.2096-4455.2019.4.028

DOI: 10.13334/j.0258-8013.pcsee.191728

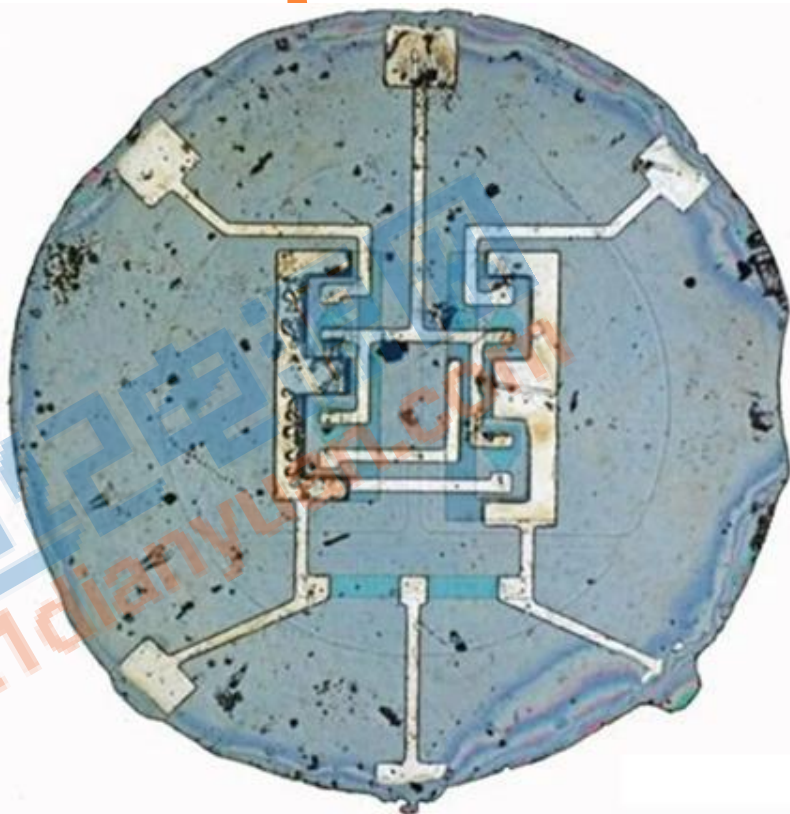
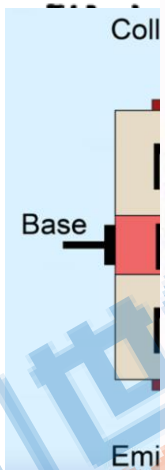
DOI: 11.11985/2016.01.001

半导体材料发展历程概述

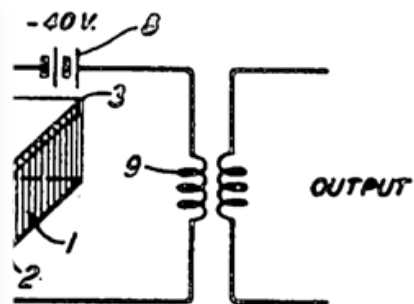


第一代、第二代、第三代

Oct. 3



UTILIZING LS 2,524,035
3 Sheets-Sheet 1

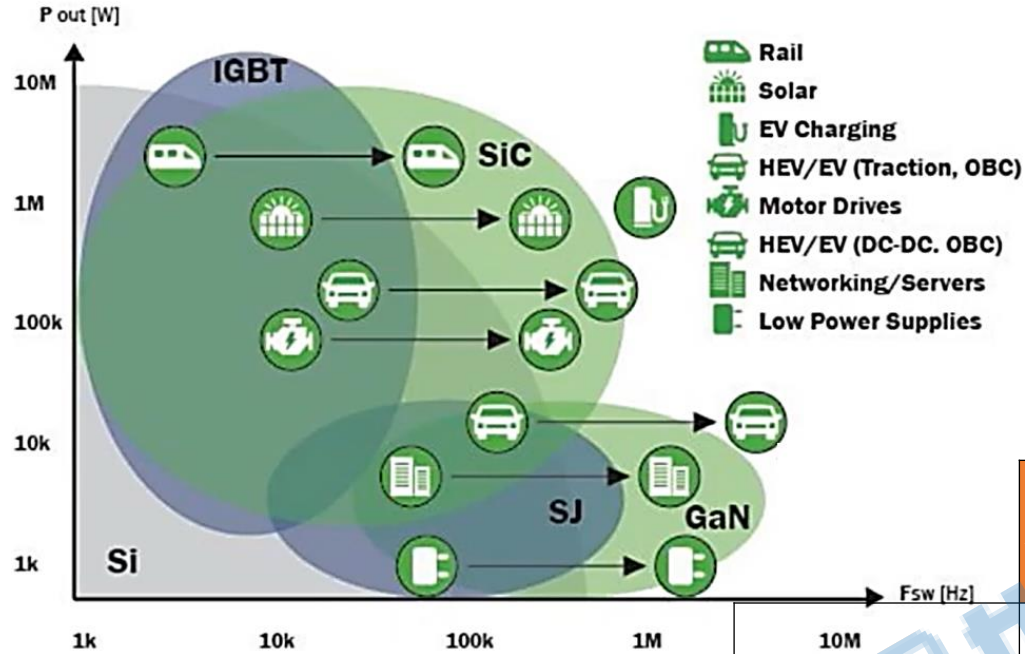


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<https://zhuanlan.zhihu.com/p/465126898>

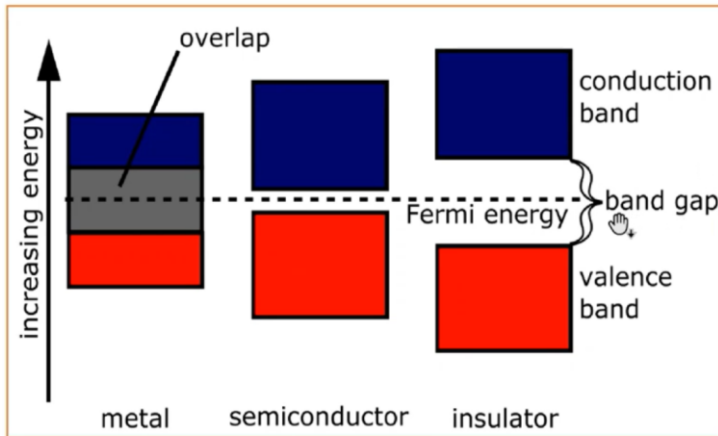
第一代半导体

半导体材料优缺点及主要应用



Commercially Available Devices

Device Technology	Working Voltage (V)
Silicon Super-Junction MOSFET	600 – 800V
Silicon IGBT	650 – 6500V
SiC MOSFET	650 – 1700V
GaN HEMT	< 650V



"A comparison of the band gaps of metals, insulators and semiconductors," by inductivelead CC A-SA 2.5

宽禁带: $E_g > 2.3 \text{ eV}$

本征半导体材料	优点	缺点	主要应用
第一代 (元素半导体) 硅 (Si) 锗 (Ge)	技术成熟; 价格便宜;	相对低的热导率; 相对低的温度范围; 相对低的电压范围;	取代了笨重的电子管, 硅基半导体材料开创了MOSFET和IGBT为代表的固态电子时代;
第二代 (化合物半导体) 砷化镓 (GaAs) 磷化铟 (InP)	高频特性; 高电流密度; 低噪声;	制造成本高; 热稳定性差;	射频、微波和光电器件; 高灵敏度传感器;
第三代 (宽禁带半导体) 碳化硅 (SiC) 氮化镓 (GaN)	更低的导通电阻; 更高的击穿电压; 更低的结-壳热阻; 更低的开关损耗;	制造难度大; 良率低;	储能、光伏、充电桩 汽车OBC/Traction/E-compressor 电池化成、特种电源 (电镀/电焊) ...

宽禁带半导体概述

参考资料:

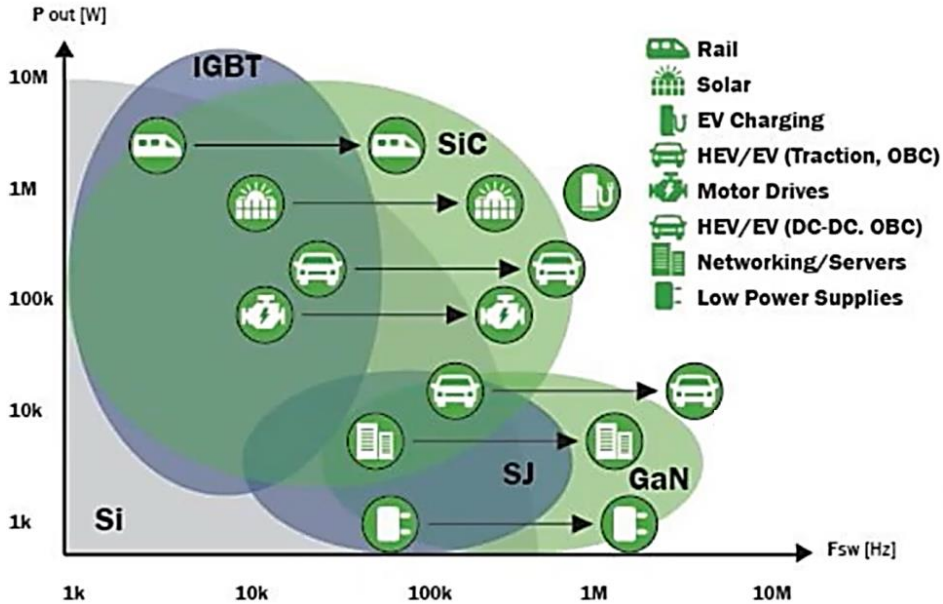
<https://www.onsemi.com/download/application-notes/pdf/and90103-d.pdf>

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DOI: 11.11985/2016.01.001

宽禁带半导体与硅参数对比



属性	硅	4H-SiC	GaN
带隙能量 (eV)	1.12	3.26	3.5
电子迁移率 (cm ² /Vs)	1400	900	1250
空穴迁移率 (cm ² /Vs)	600	100	200
击穿场 (MV/cm)	0.3	3	3
热导率 (W/cm ² °C)	1.5	4.9	1.3
最高结温 (°C)	150	600	400

SiC VS. Si

- 千分之一的比导通电阻；
- 十倍的击穿场强；
- 四倍的热导率；
- 三倍的禁带宽度；

- **更宽**的带隙能量意味着能够承受**更高**的击穿电压
- **相同**数量级的迁移率意味着**适合**高频开关应用场景
- **更高**的击穿场意味着**更小**器件厚度和导通电阻
- **更高**的热导率意味着**更低**温升
- **更高**的结温意味着**更适合**高温大电流应用场景

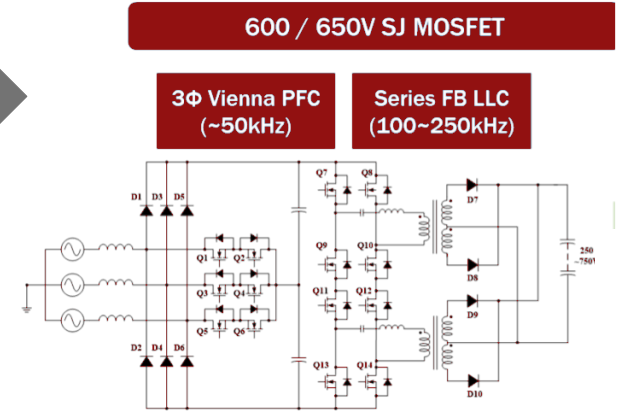
碳化硅器件较硅基器件优势

更低的损耗 → 更高的效率



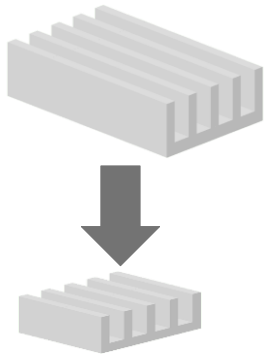
系统级
- 小型化
- 轻质化
- 成本效益

简化拓扑
: 更低的 $R_{ds(on)}$
和更高的耐压

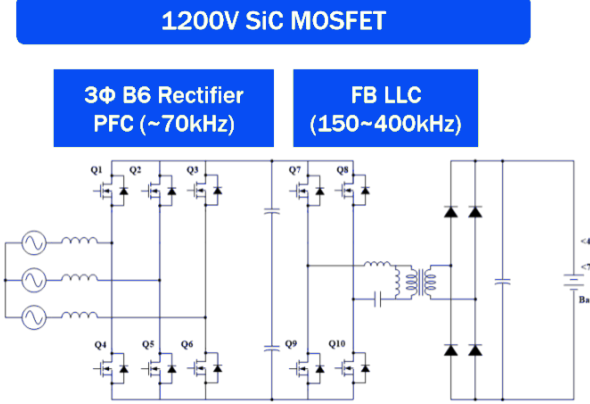


更小尺寸的散热器

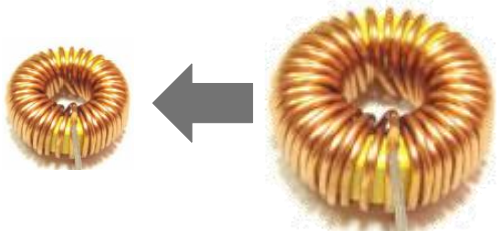
更好的导热效果



更高的开关频率



更小的被动器件

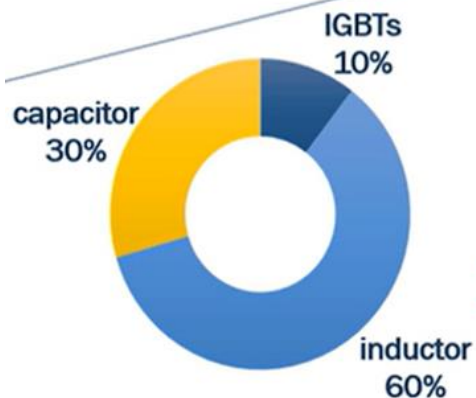




碳化硅方案系统级优势

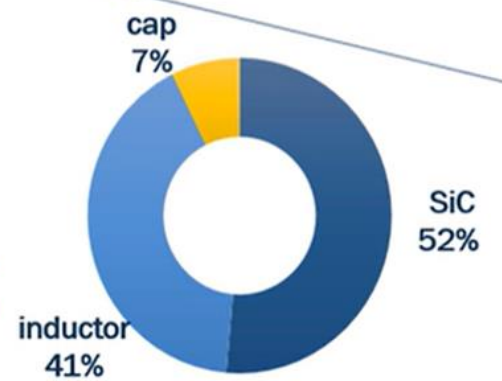
- 小型化
- 轻质化
- 成本效益

Si vs SiC 30KW Inverter BOM



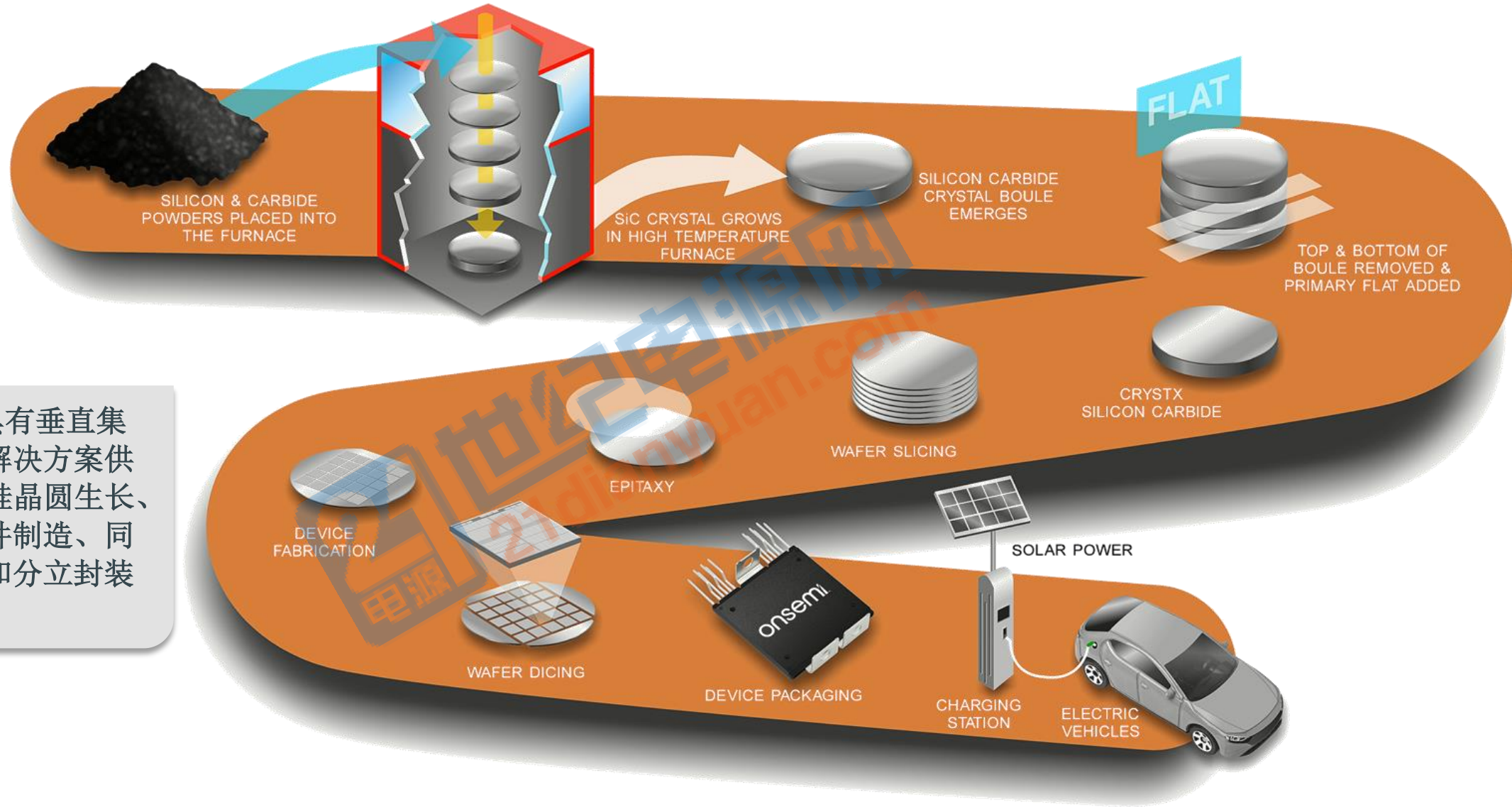
20KHz Si IGBT Solution	
24 IGBTs	\$ 48
Inductors	\$ 276
Capacitors	\$ 135
TOTAL BOM COST	\$ 460

80KHz SiC MOSFET Solution	
24 SiC MOSFET's	\$ 230
Inductors(75% smaller in value)	\$ 193
Caps (75% smaller in value)	\$ 33
TOTAL BOM COST	~ \$ 450



图片摘自 <https://www.onsemi.com/design/resources/video-library/utilizing-wide-bandgap-wbg-in-solar-and-renewable-energy-applications>

onsemi Silicon Carbide Manufacturing Life Cycle



onsemi 是一家具有垂直集成能力的碳化硅解决方案供应商，包括碳化硅晶圆生长、衬底、外延、器件制造、同类最佳集成模块和分立封装解决方案

SiC MOSFET应用设计

碳化硅关键参数

参考资料:

<https://www.onsemi.com/download/application-notes/pdf/and90103-d.pdf>

DOI: 10.19772/j.cnki.2096-4455.2019.4.028

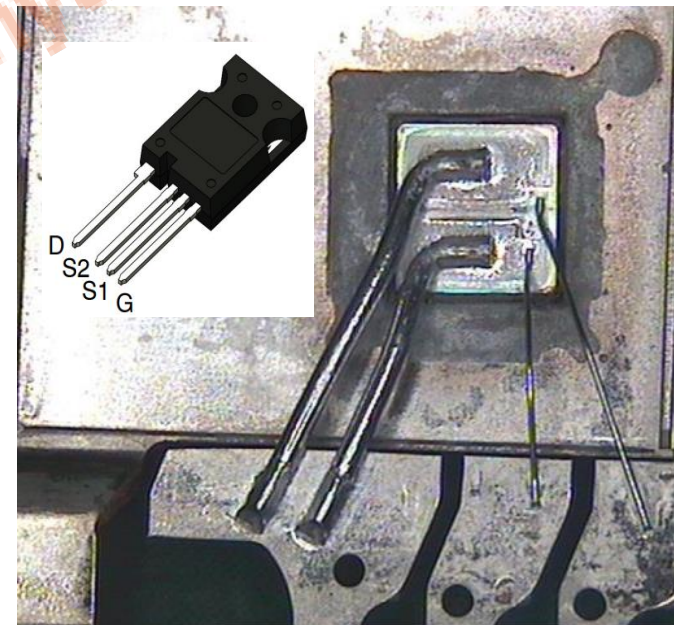
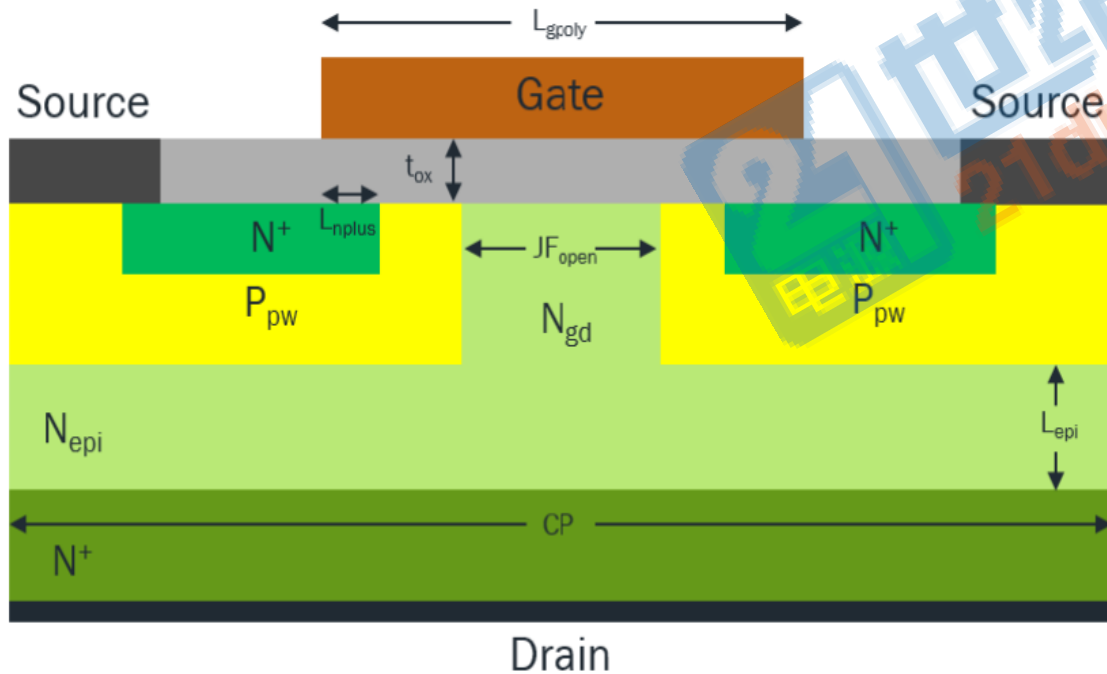
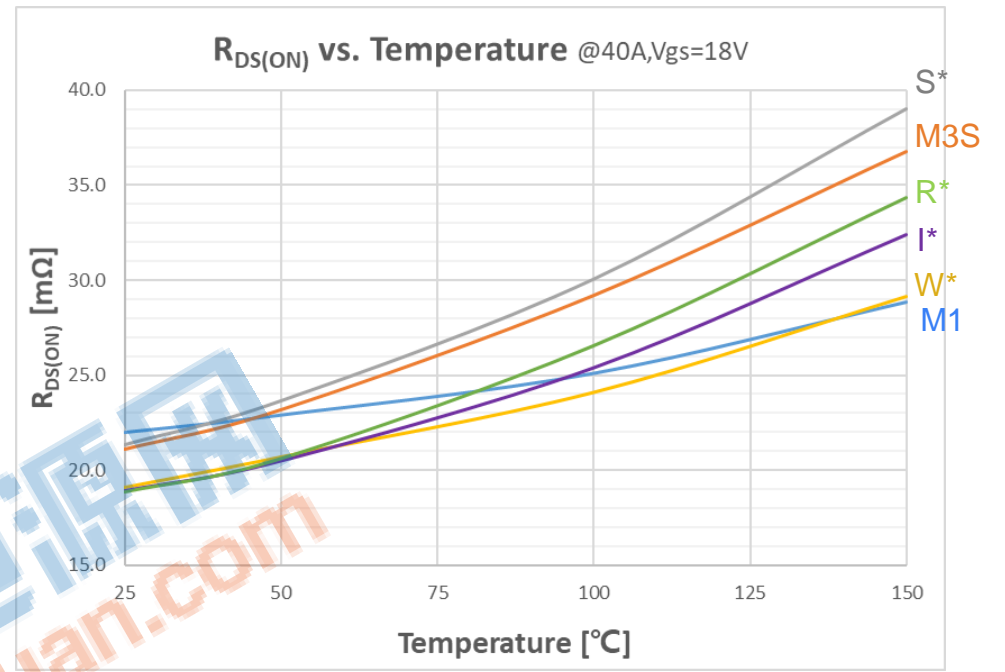
DOI: 10.13334/j.0258-8013.pcsee.191728

DOI: 11.11985/2016.01.001

碳化硅MOSFET常见静态参数

R_{ds(on)} 温度系数

- 沟道电阻: **NTC**
- JFET区电阻: **PTC**
- 漂移区电阻: **PTC**



$$P_{loss} = P_{cond} + P_{sw}$$

光伏储能、EVC等高频开关应用中功率器件的开关损耗占主导 → **M3S Win**

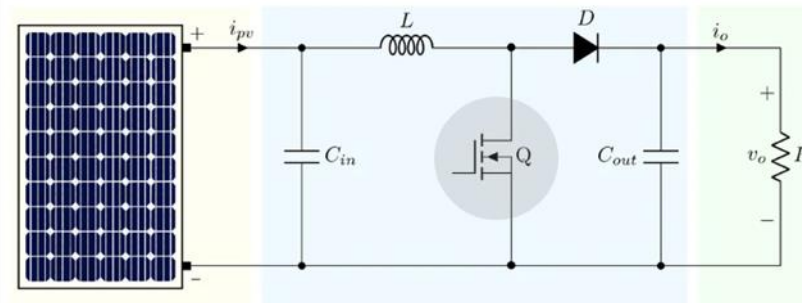
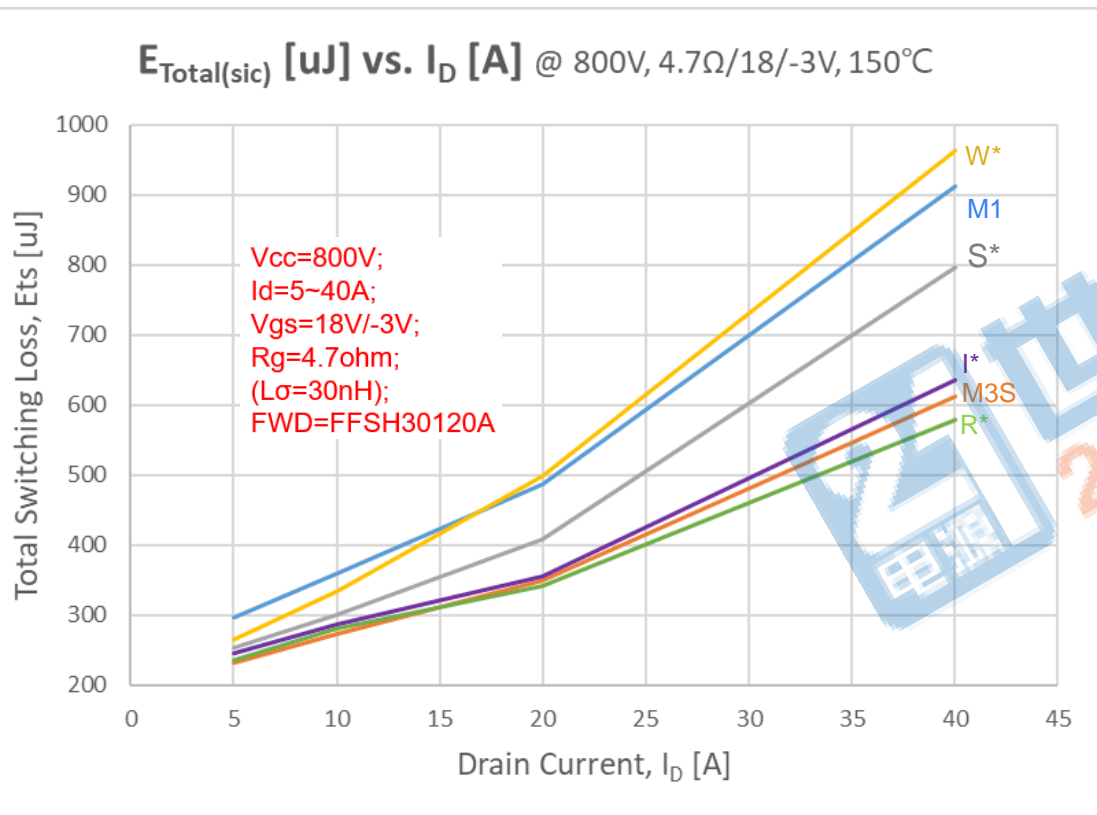
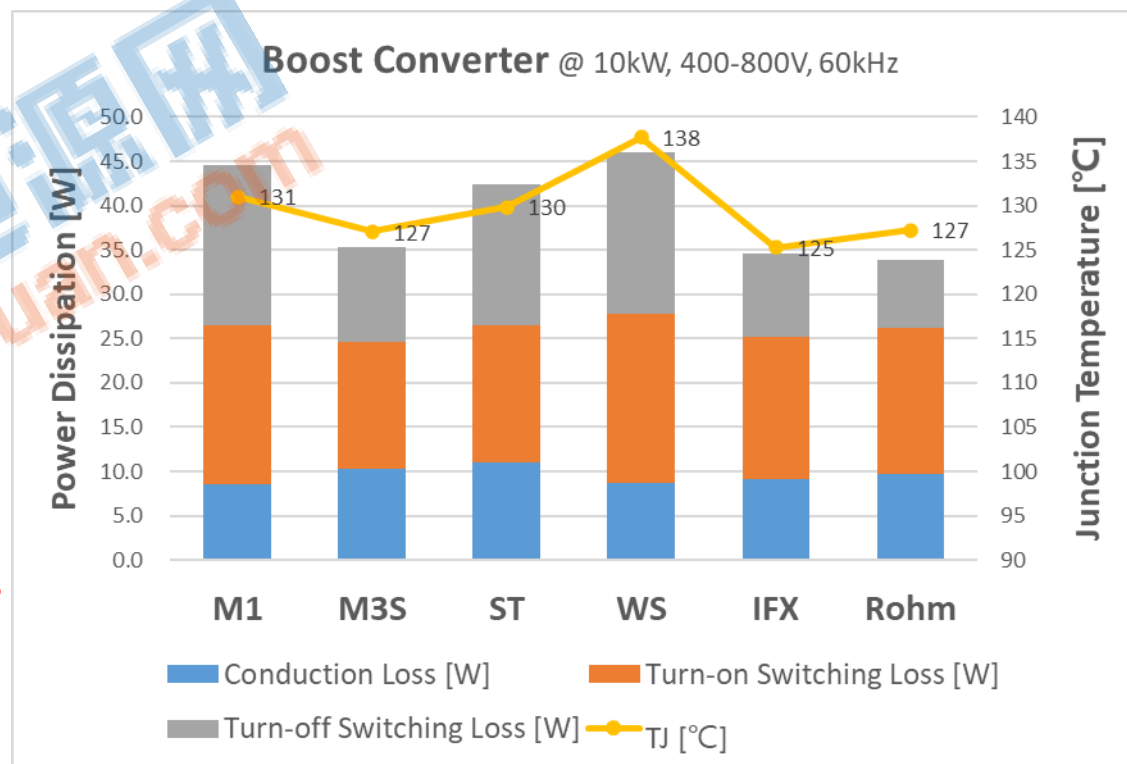


Image from <https://latexdraw.com/draw-a-dc-dc-boost-converter-in-latex-using-circuitikz/>



$V_{in}=400V$
 $V_o=800V$
 $P_o=10kW$
 $f_{sw}=60kHz$
 $V_{gs}=-3/18V$
 $R_g=4.7Ohm$
 $FWD=SiC-SBD$
 $T_{sink}=90\ deg.C$
 $R_{thcs}=0.62K/W$
 $R_{thjc}=\max\ in\ DS$



碳化硅MOSFET常见静态参数

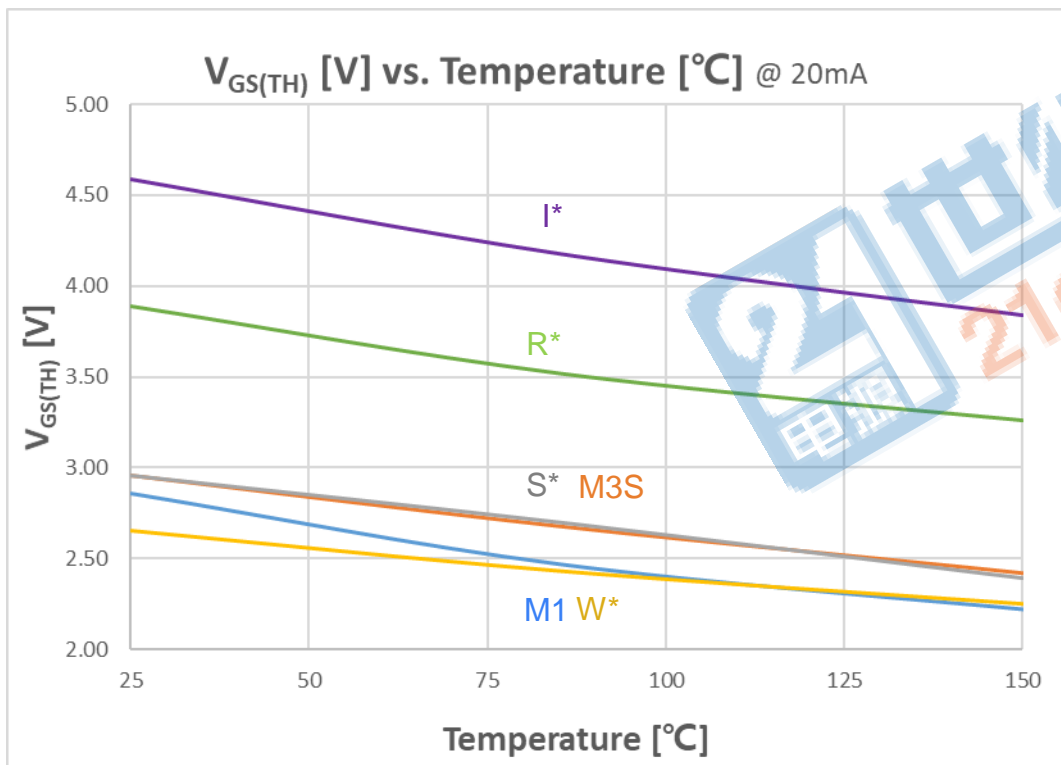
$V_{GS(TH)}$ 温度依赖性 \rightarrow NTC

相同工艺水平下，栅极阈值电压越低则比导通电阻越小，即 **$V_{GS(TH)}$ 与 R_{SP} 呈正相关**；

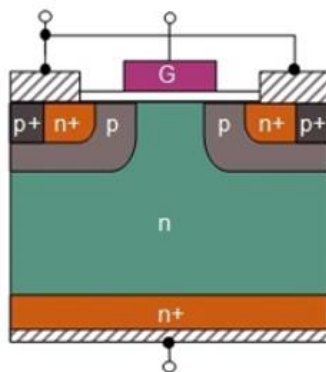
工艺限制

较低的 $V_{GS(TH)}$ 会导致较差的抗噪声能力

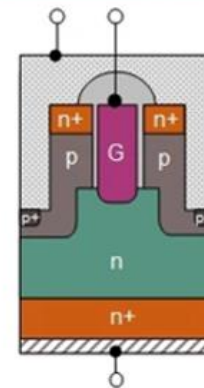
- 米勒电容由 dv/dt 引起的感应电流尖峰导致误导通；
- 公共源极寄生电感由 di/dt 引起的感应电压尖峰导致误导通；
- 寄生电感与寄生电容之间的谐振振荡；



SiC Planar



SiC Trench

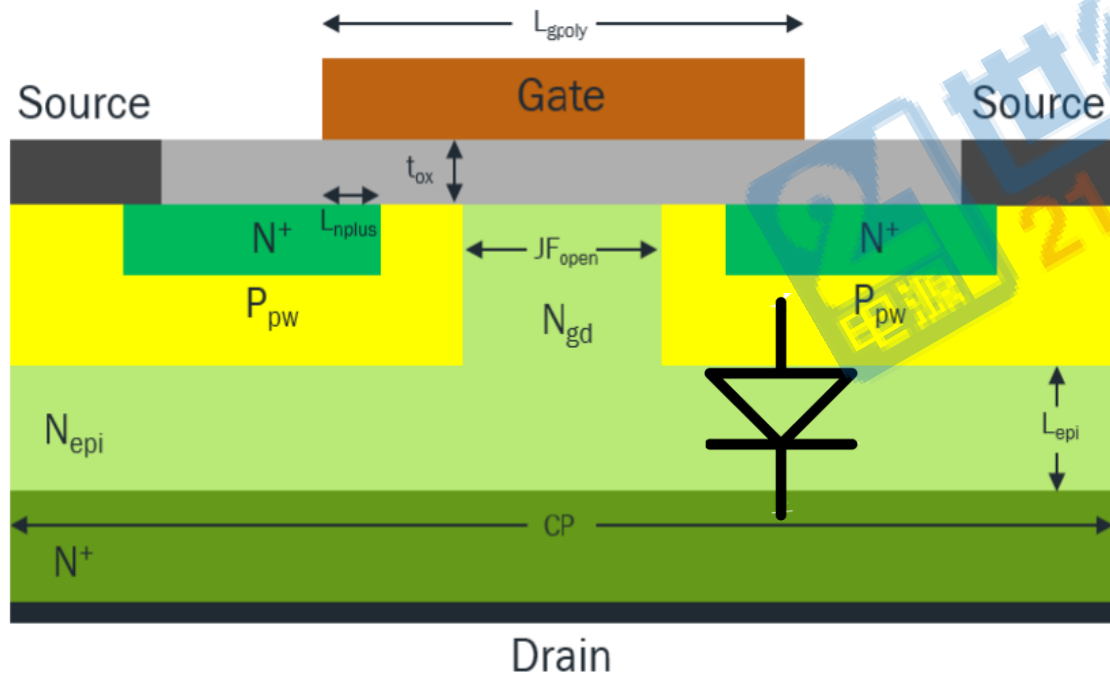


碳化硅MOSFET常见静态参数

$V_{GS(OP)}$ 推荐栅源工作电压

- $R_{DS(ON)}$ → 漏源导通电阻;
- E_{ON} 、 E_{OFF} → 开关损耗;
- V_F → 体二极管正向压降; **工艺限制**
- E_{REC} → 体二极管反相恢复损耗;
- 栅氧可靠性;

- 更高的 $V_{GS(OP)}$ 要求更大的额定值裕量;
- 栅氧层厚度加厚会降低沟道迁移率和跨导率、减慢开关速度;

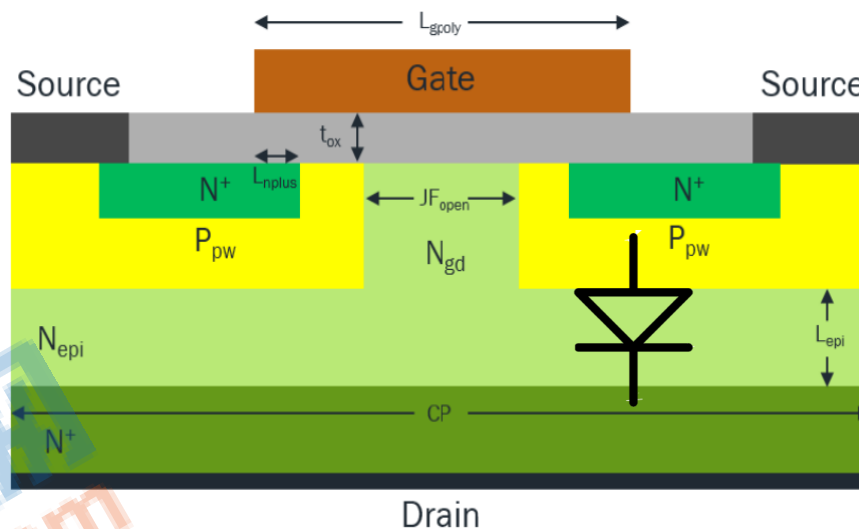


Key Parameters @ conditions, RT		NTH4L040N120M3S	C3M0040120K
$V_{GS(OP)}$ [V]		18V/-3V	15V/-4V
$V_{GS(max)}$ [V]		22V/-10V	19V/-8V
$R_{ds(on)}$ [mΩ]	@ $V_{GS}=18V/15V$; $I_D=30A$; $T_J=25^{\circ}C$	40	40
$R_{ds(on)}$ [mΩ]	@ $V_{GS}=18V/15V$; $I_D=30A$; $T_J=150^{\circ}C$	62	61
Q_g [nC]	@ 800V, 30A/40A, $V_{GS}=18/-3V \rightarrow$ onsemi; $V_{GS}=15/-4V \rightarrow$ Wolfspeed	107	118

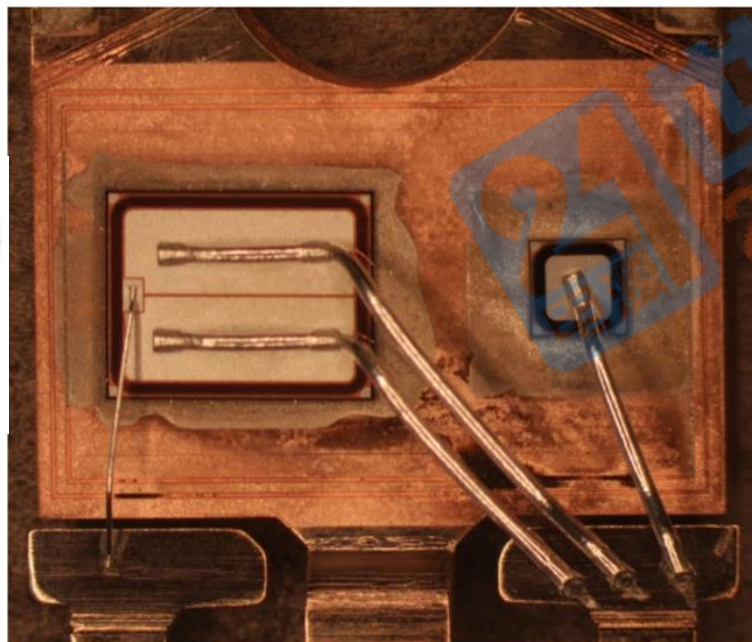
碳化硅MOSFET常见静态参数

V_F 体二极管导通压降

- NTC;
- V_F 更大相比硅 MOSFET体二极管;
- E_{rec} 更小相比硅 MOSFET体二极管;

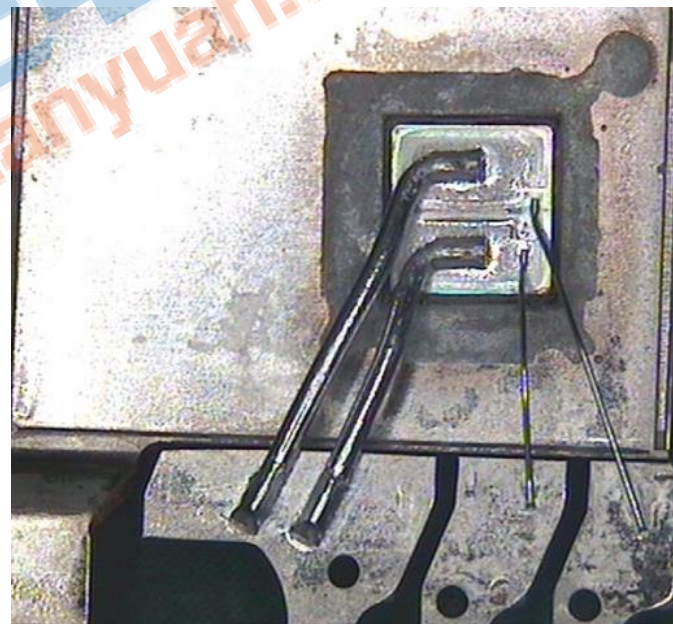


IGBT内部晶圆

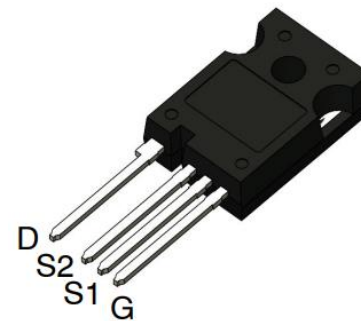


图片摘自www.onsemi.com-AND9140-D

SiC MOSFET内部晶圆



SiC MOSFET破坏性测试光学图片



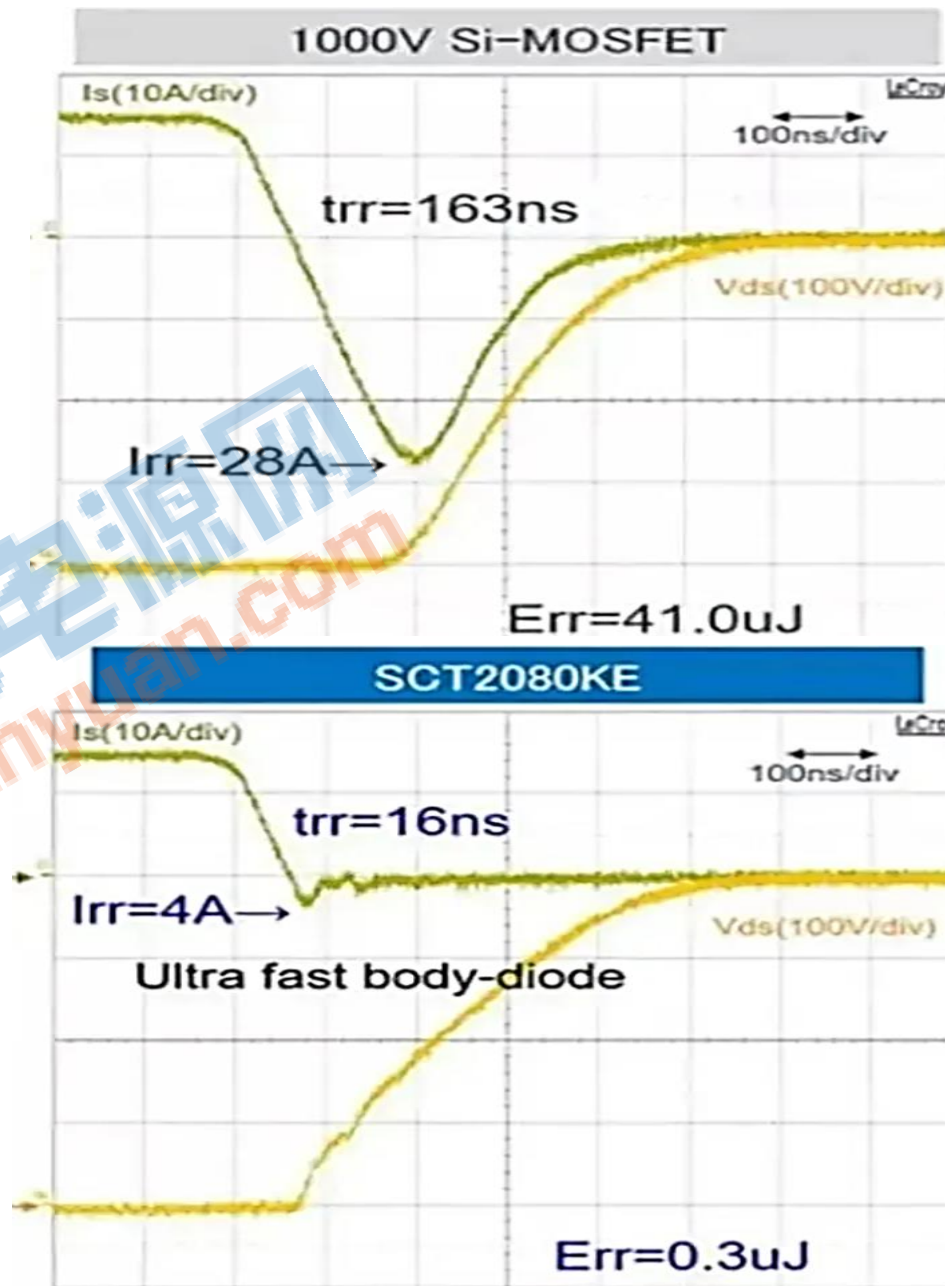
碳化硅MOSFET体二极管导通压降

类别	V _F 导通压降 typical@25°C
硅 PN 结二极管	1.5 V ~ 3 V
碳化硅 SBD	1.38 V ~ 1.75 V
C3M0032120K	4.2 V ~ 4.6 V
IMZA120R030M1H	3.6 V ~ 5.0 V
NTH4L030N120M3S	4.6 V
IGBT体二极管	1.5 V ~ 2 V
IGBT SiC SBD	1.45 V ~ 1.80 V

SCT2080KE Datasheet

●Body diode electrical characteristics (Source-Drain) (T_a = 25°C)

Parameter	Symbol	Conditions	Values			Unit
			Min.	Typ.	Max.	
Body diode continuous, forward current	I _S ^{*1}	T _c = 25°C	-	-	40	A
Body diode direct current, pulsed	I _{SM} ^{*2}		-	-	80	A
Forward voltage	V _{SD} ^{*4}	V _{GS} = 0V, I _S = 10A	-	4.6	-	V
Reverse recovery time	t _{rr} ^{*4}	I _F = 10A, V _R = 400V di/dt = 150A/μs	-	31	-	ns
Reverse recovery charge	Q _{rr} ^{*4}		-	44	-	nC
Peak reverse recovery current	I _{rrm} ^{*4}		-	2.3	-	A



<https://zhuanlan.zhihu.com/p/573910994>

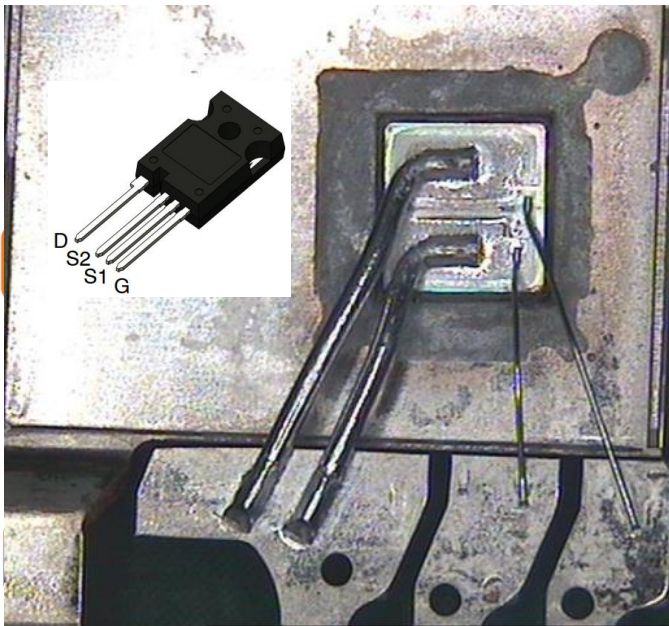
碳化硅MOSFET关键参数

$$R = \rho \times L \div S$$

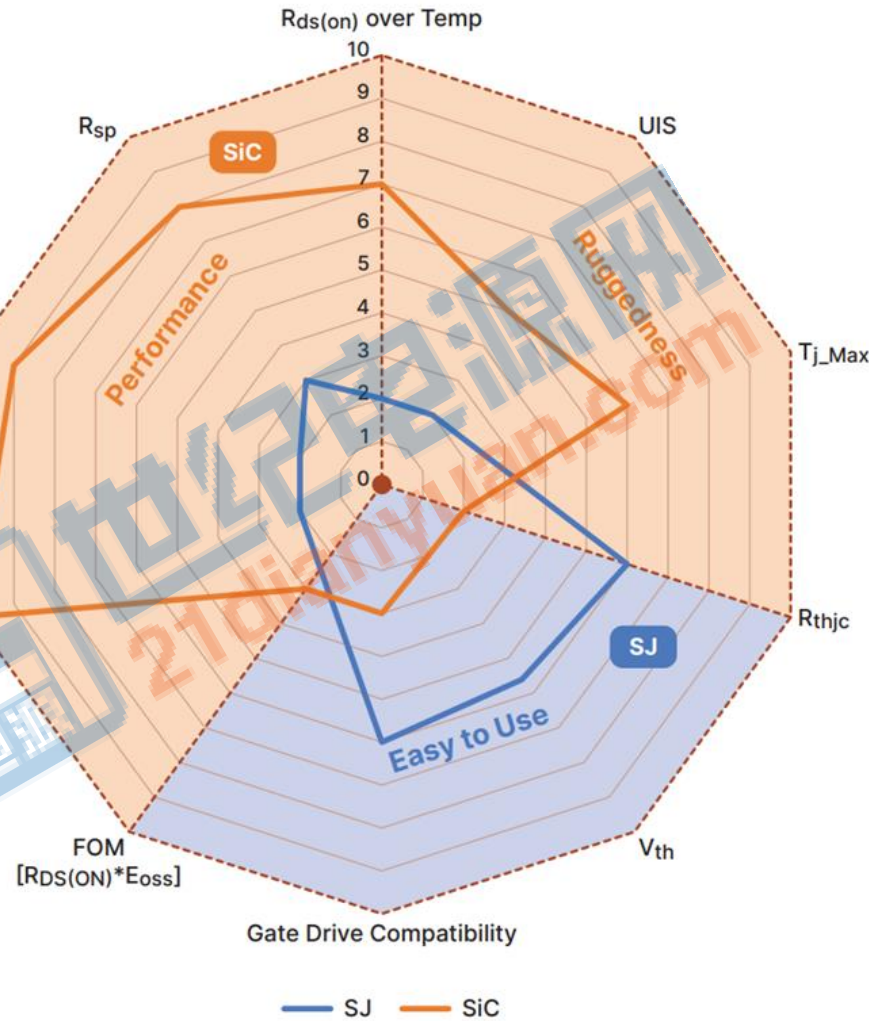
$$R_{sp} = R_{ds} \times S$$

R_{sp}

- Lower value is better
- Winner: **SiC**
- SJ Tech is limited by Si



$$E_{oss} = Q_{oss} \times V_{ds}$$



- $R_{ds(ON)}$ over Temp**
 - Lower value is better for $P_{con}@high T$
 - Winner: **SiC**
 - SJ is limited by Si material
- UIS**
 - Higher value is better
 - Winner: **SiC**
- R_{thjc}**
 - Lower value is better
 - Winner: **SJ**
 - Larger die size of SJ
- V_{th}**
 - Higher value is better for immunity
 - Winner: **SJ**
 - Related false turn-on → Increasing P_{loss} and failure
- Gate Drive Compatibility**
 - Gate drive voltage
 - Winner: **SJ (0 to 12 V)**
 - SiC (-5 to 18 V/0 to 18 V)

SiC MOSFET应用设计

SiC MOSFET并联影响与栅极电阻设置

参考资料:

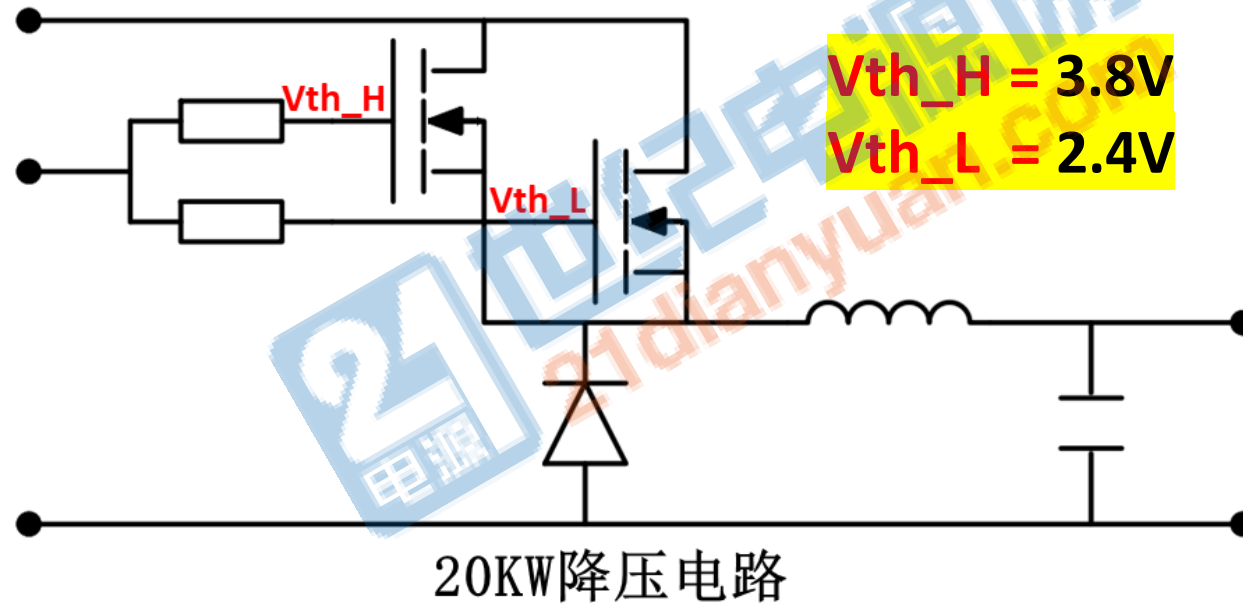
<https://www.onsemi.com/download/application-notes/pdf/and90103-d.pdf>;

[TND6440 - Paralleling SiC MOSFETs Process Impacts and Gate Resistors Setup \(onsemi.com\)](#);

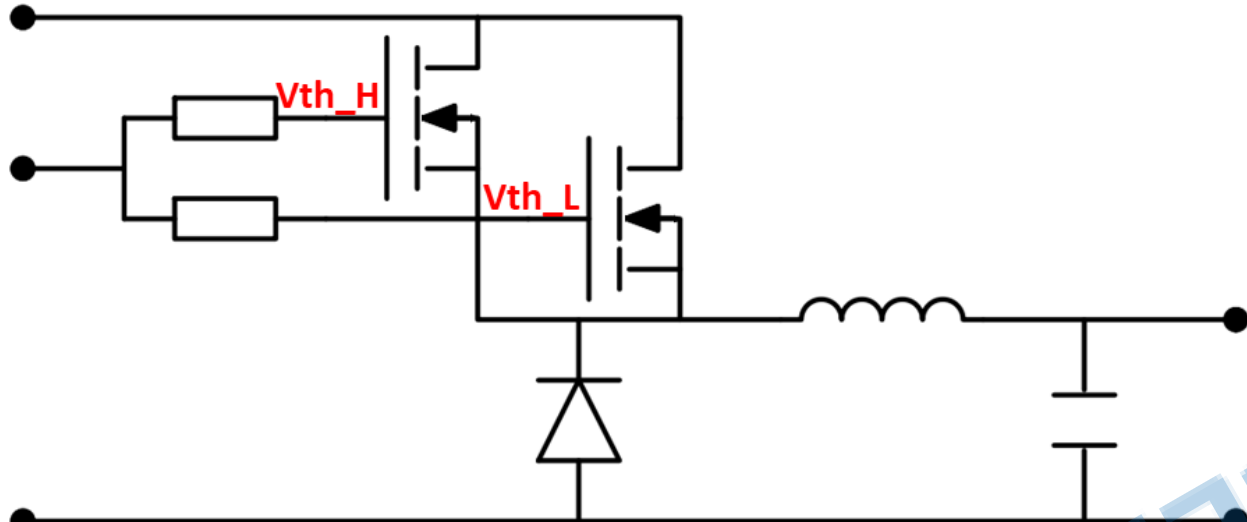
<https://ieeexplore.ieee.org/document/7931077/>;

<https://www.onsemi.com/download/application-notes/pdf/and90255-d.pdf>;

工艺参数 (V_{th}) 不一致的SiC MOSFET并联会发生什么？

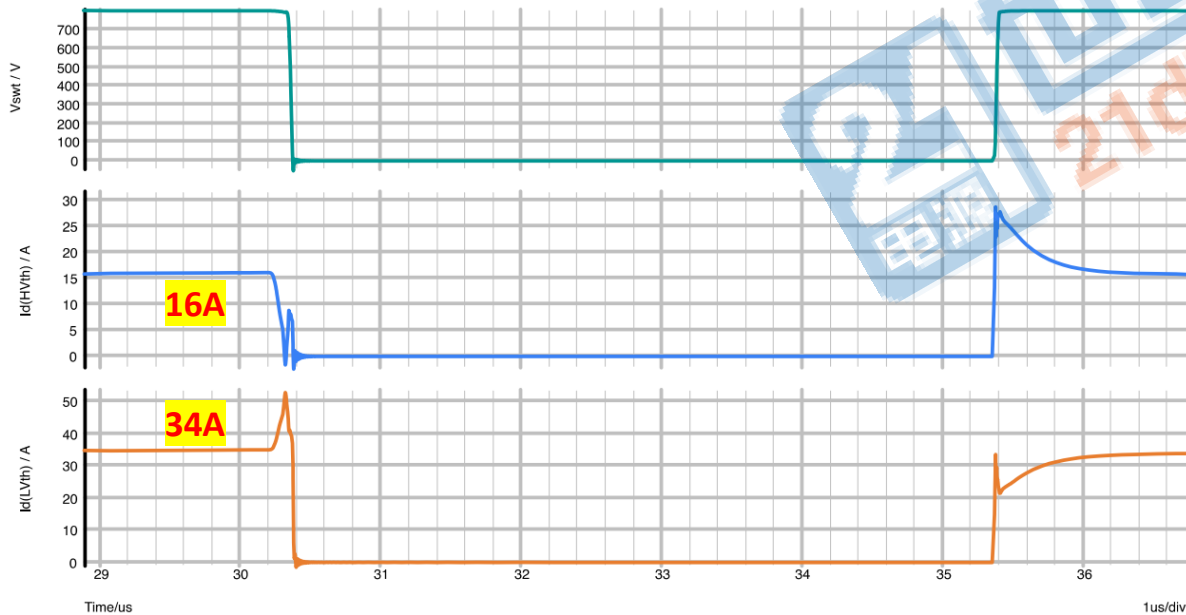


SiC MOSFET 并联影响与栅极电阻设置



$V_i = 800V$
 $V_o = 400V$
 $R_g = 10\Omega$
 $F_{sw} = 100KHz$
 $V_{th_H} = 3.8V$
 $V_{th_L} = 2.4V$

20KW 降压电路



IEEE Xplore

Conferences > 2020 32nd International Sympo...

SiC MOSFET Corner and Statistical SPICE Model Generation

Publisher: IEEE

Canzhong He; James Victory; Yunpeng Xiao; Herbert De Vleeschouwer; Elvis Zheng; ZhiPing Hu

7 Cites in Papers | 948 Full Text Views

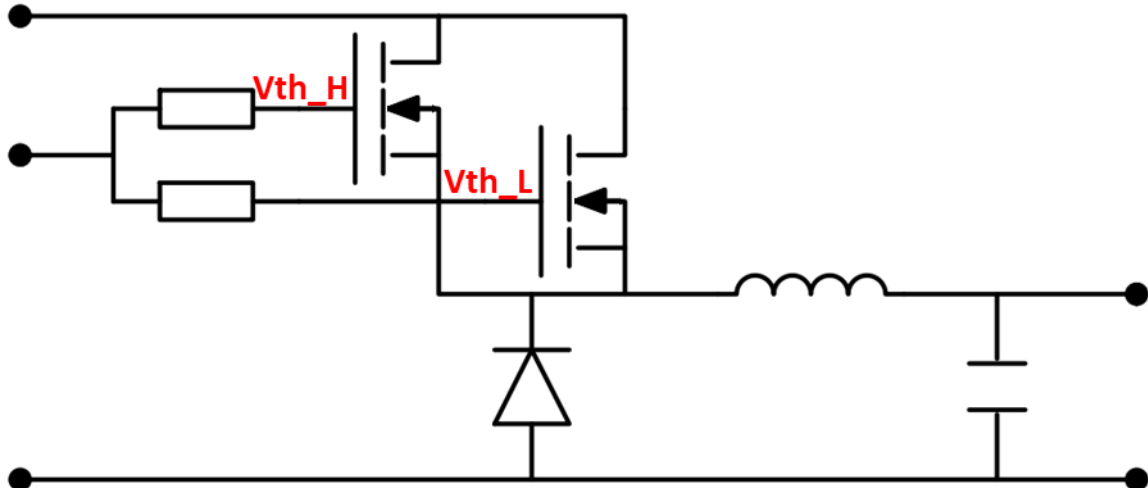
Abstract: This paper presents a novel approach to generate corner and statistical SPICE models for SiC MOSFETs. The technique is derived from the mature IC industry standard approach known as Backward Propagation of Variance. Physically based, scalable SiC MOSFET SPICE models are required to simulate the correlations between electrical specifications and process variations. The methodologies presented are applicable to other power discrete devices such as super-junction MOSFETs, IGBTs, and GaN HEMTs.

Published in: 2020 32nd International Symposium on Power Semiconductor Devices and ICs (ISPSD)

Date of Conference: 13-18 September 2020
Date Added to IEEE Xplore: 18 August 2020

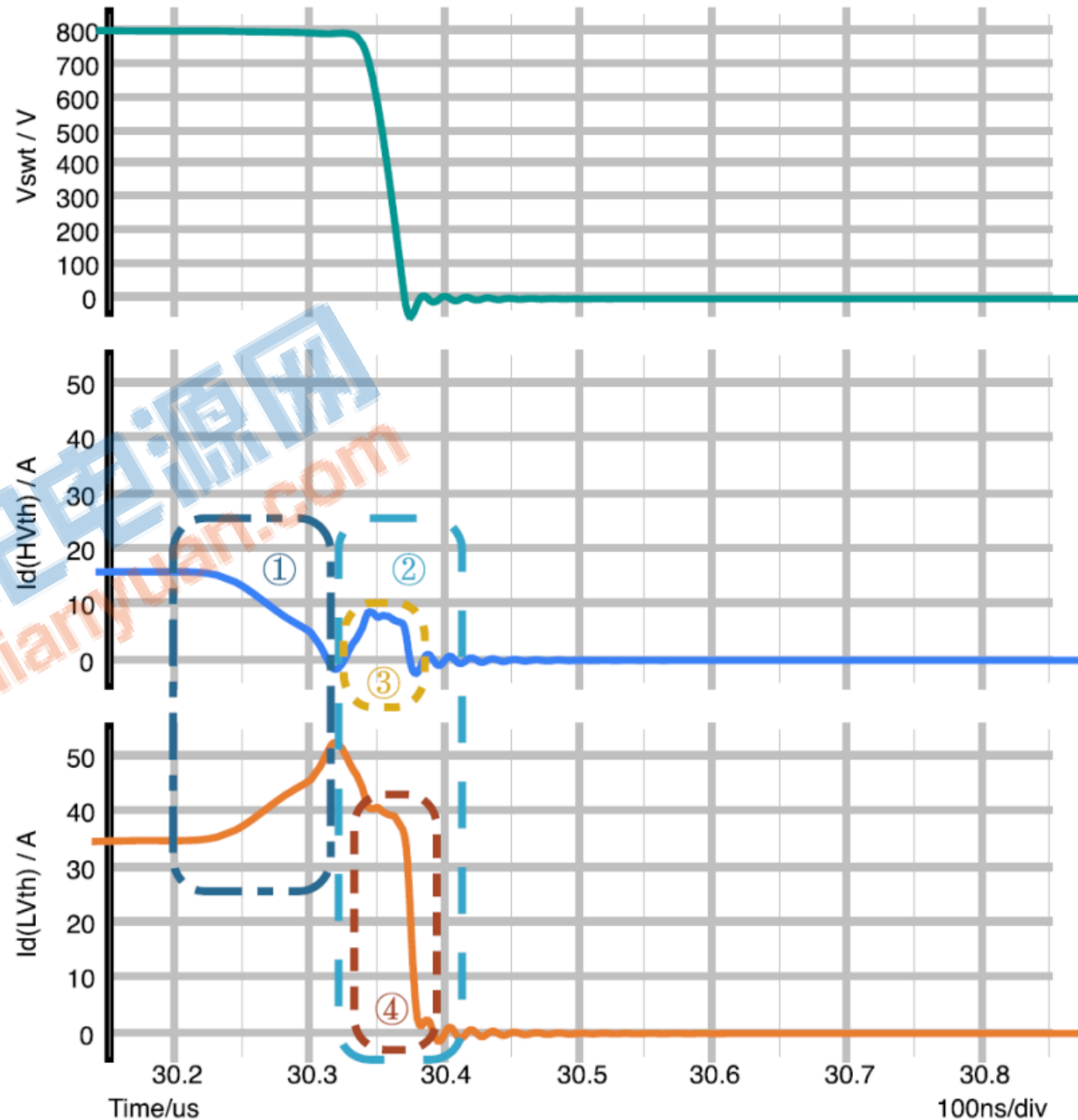
DOI: 10.1109/ISPSD46842.2020.9170091
Publisher: IEEE
Conference Location: Vienna, Austria

关断电流波形

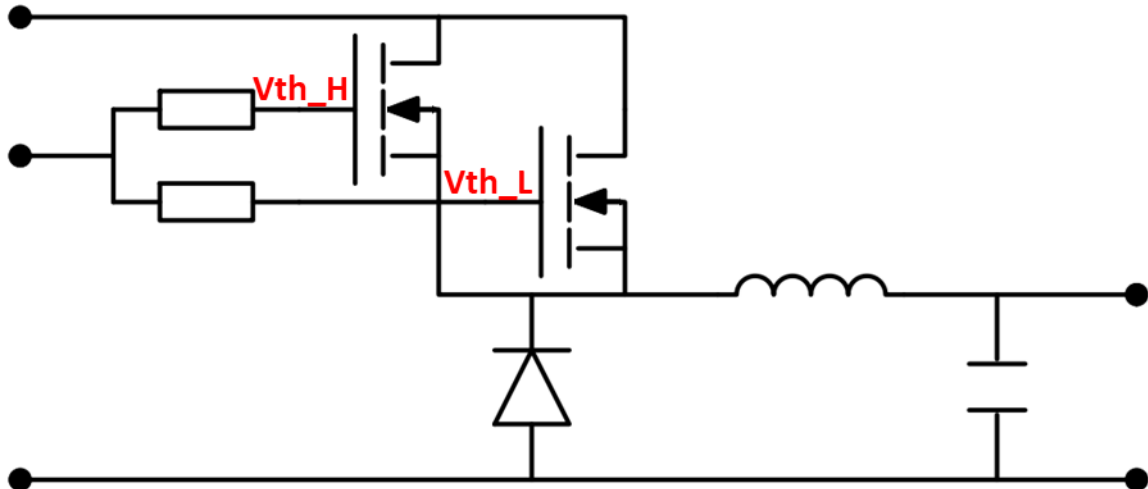


20KW降压电路

- ① Vth_H器件先关断，电流全部转移到Vth_L器件；
- ② Vth_L器件延迟关断；
- Vth_H器件Cds结电容充电引起电流尖峰；
- ③ Id电流变化发生在开关节点过渡期间；
- ④ Vth_L器件Cds充电电流与逐渐减小的漏极电流混合；

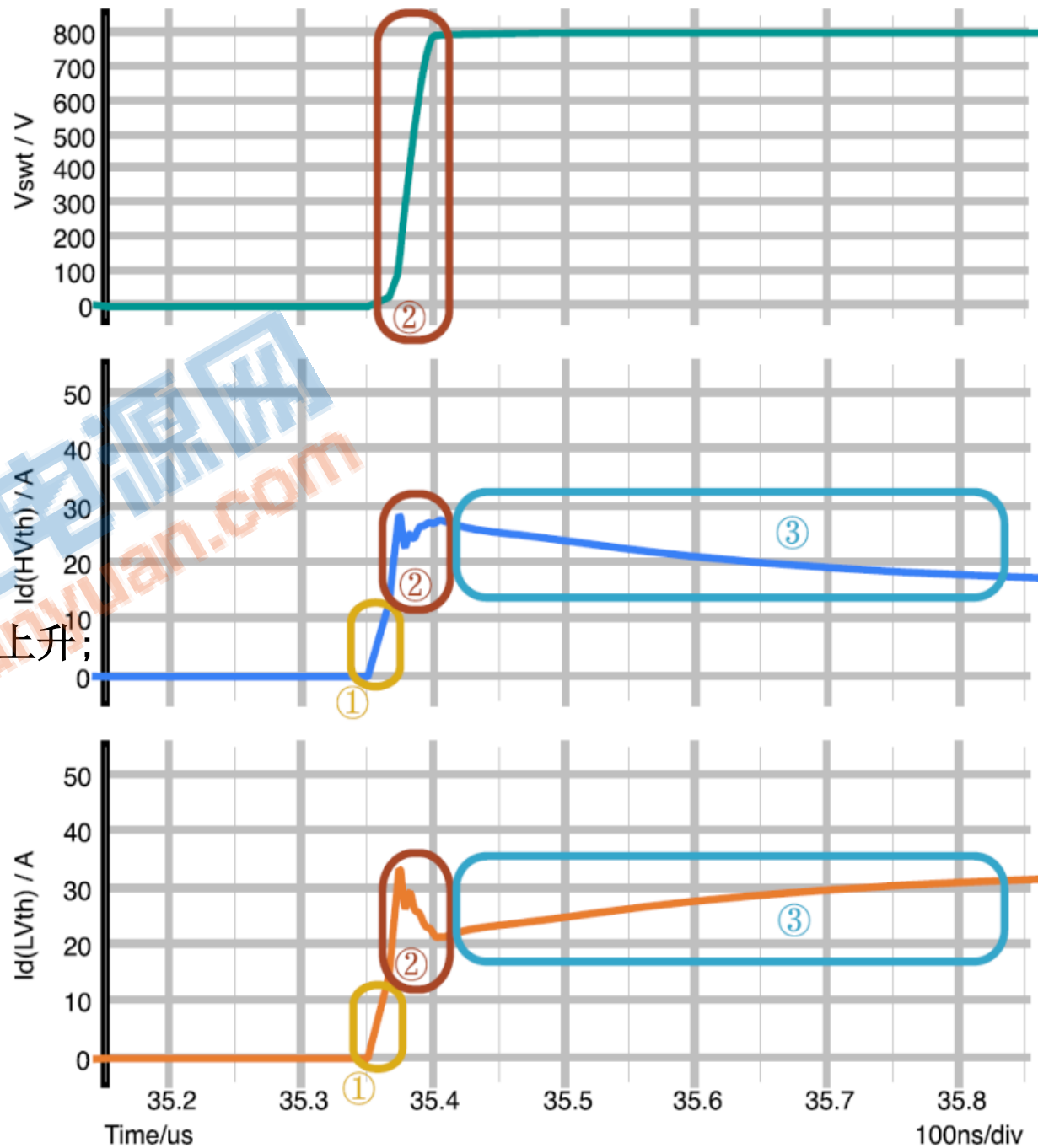


开通电流波形



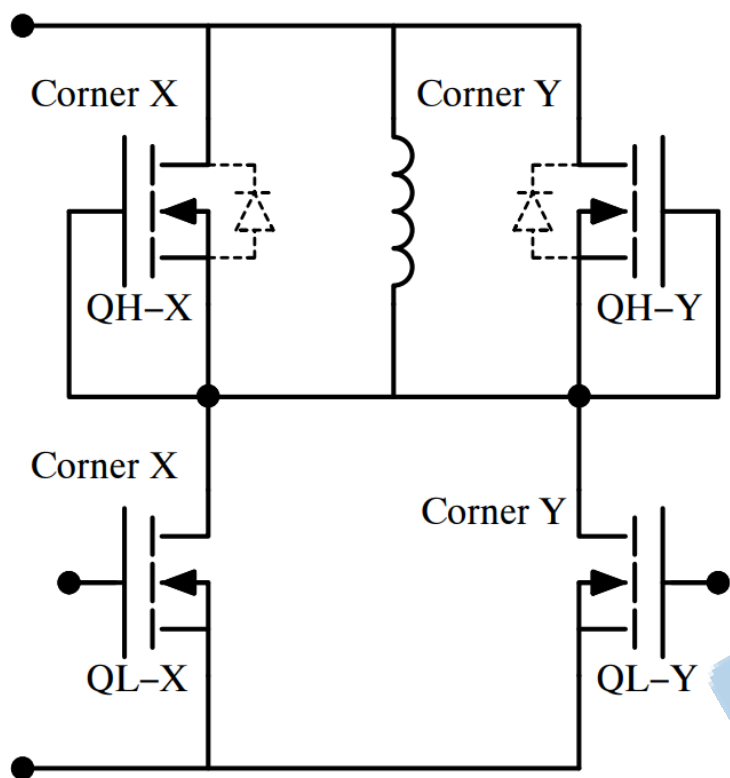
20KW降压电路

- ① 在到达密勒平台之前两器件导通电流以大致相同的斜率上升;
- ② 进入密勒平台, 时间等于开关节点电压过渡时间; 尖峰由SBD截至寄生结电容充放电电流引起;
- ③ V_{gs} 的继续增加, 并联器件 $R_{ds(on)}$ 进入可变电阻区;



Case	Eon	Eoff	Peak Current before Miller Plateau	Peak Current after Miller Plateau	Current during ON-Time	Total Losses
LVth	380 μ J	650 μ J	33.5 A	28 A	34 A	105 W
HVth	350 μ J	100 μ J	28.5 A	22 A	16 A	45 W

DPT平台-改变栅极电阻

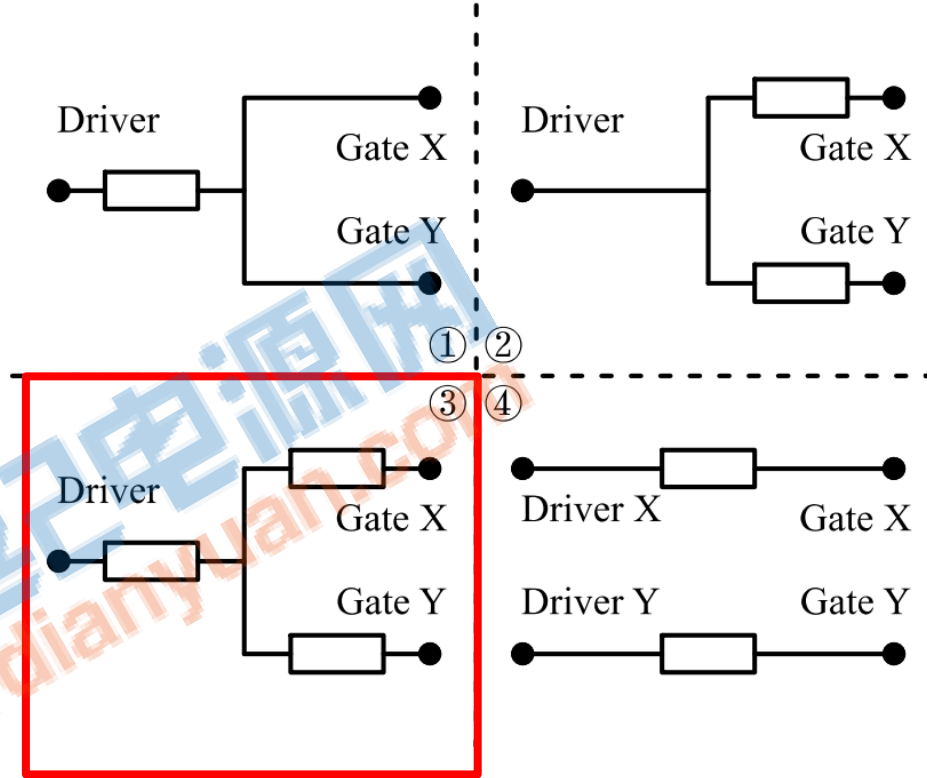


$V_{bus} = 800V$

$I_L = 100A$

$V_{th_H} = 3.8V$

$V_{th_L} = 2.4V$

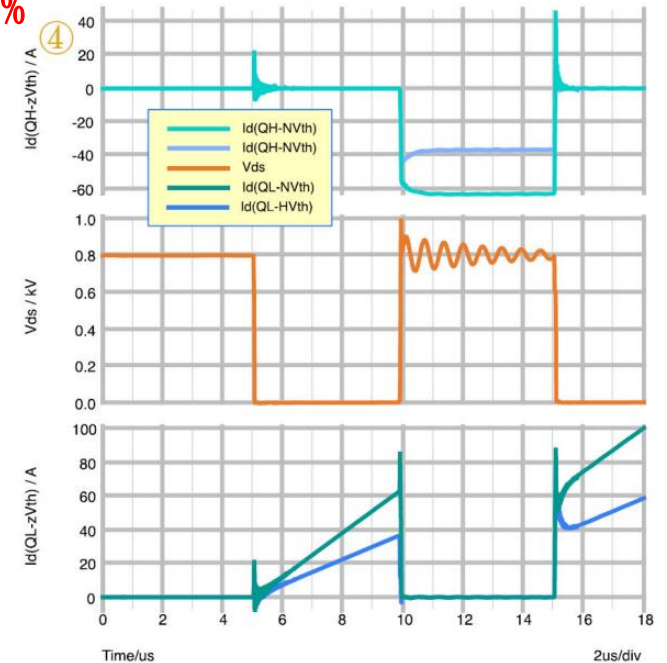
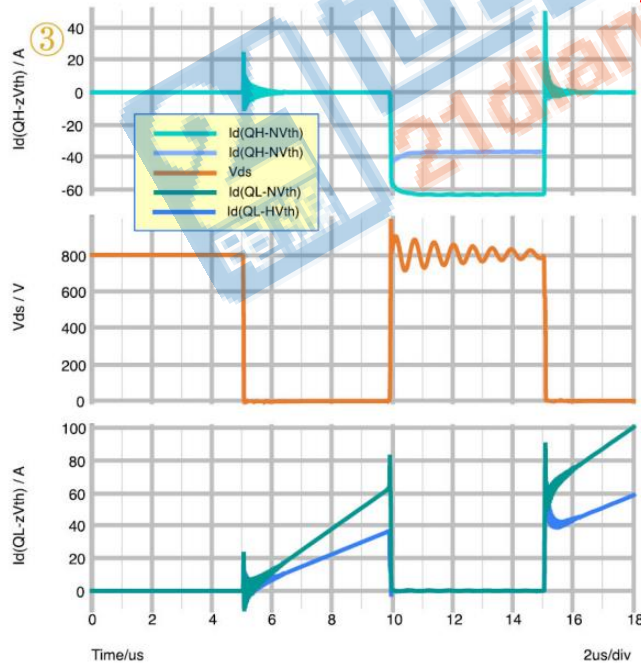
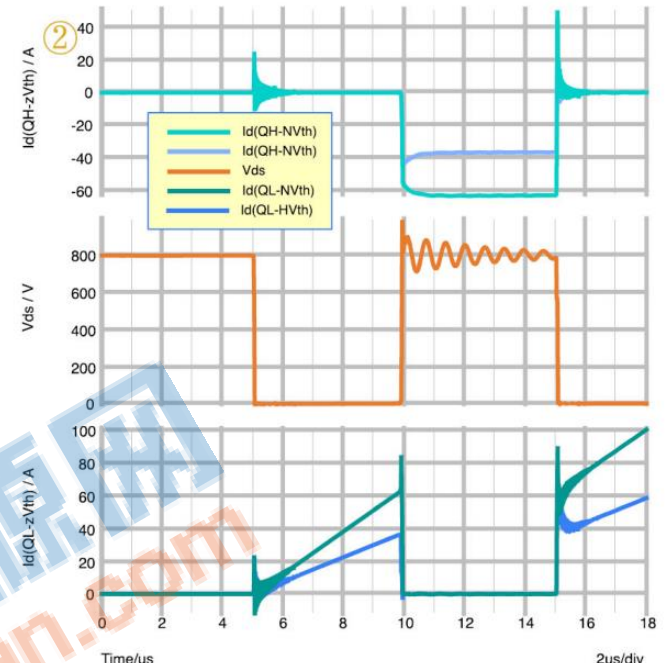
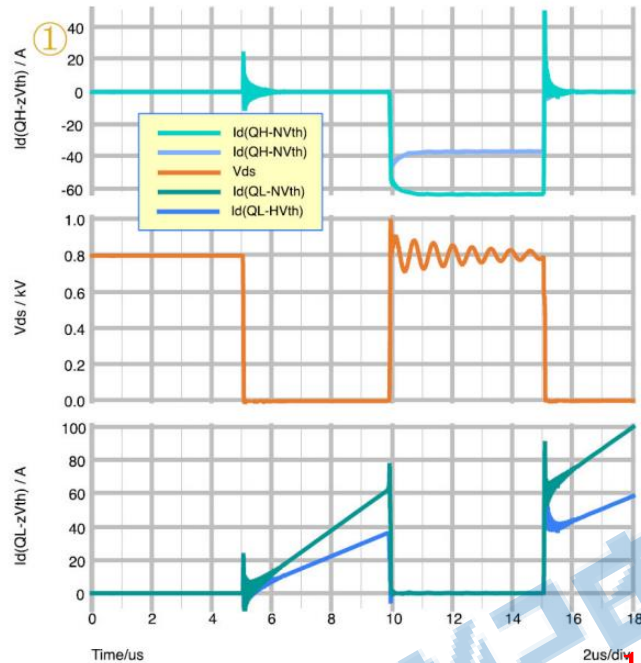
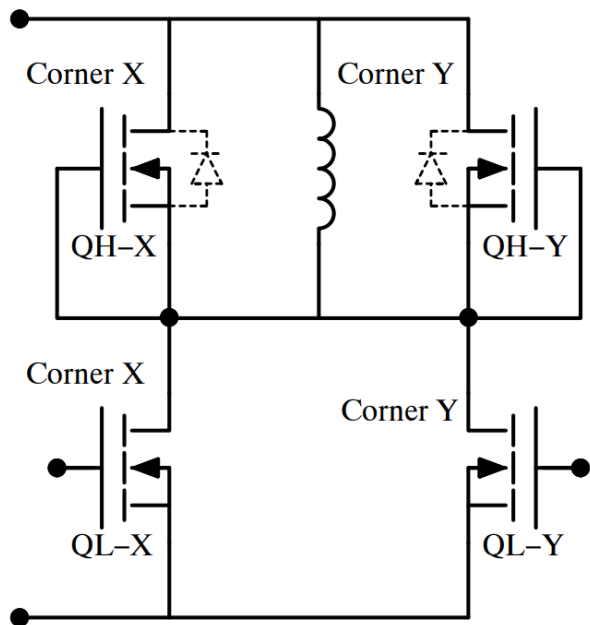


实现0%~100%的栅极分流比率;

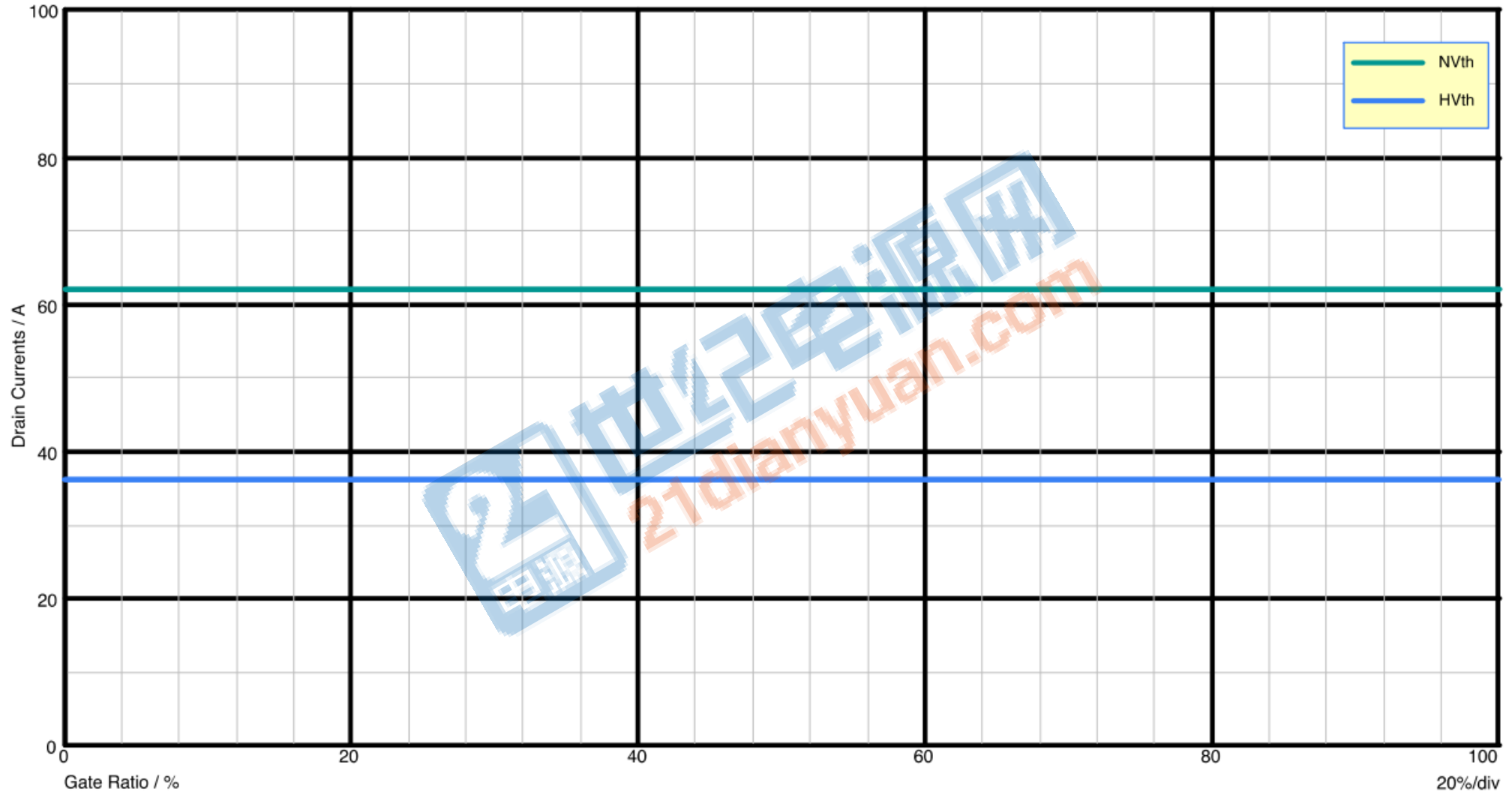
0% → 只有公共电阻;

100% → 只有栅极电阻, 无公共电阻

DPT测试结果



栅极电流



开关损耗



SiC MOSFET应用设计

V_{gs}=0V驱动设计

参考资料:

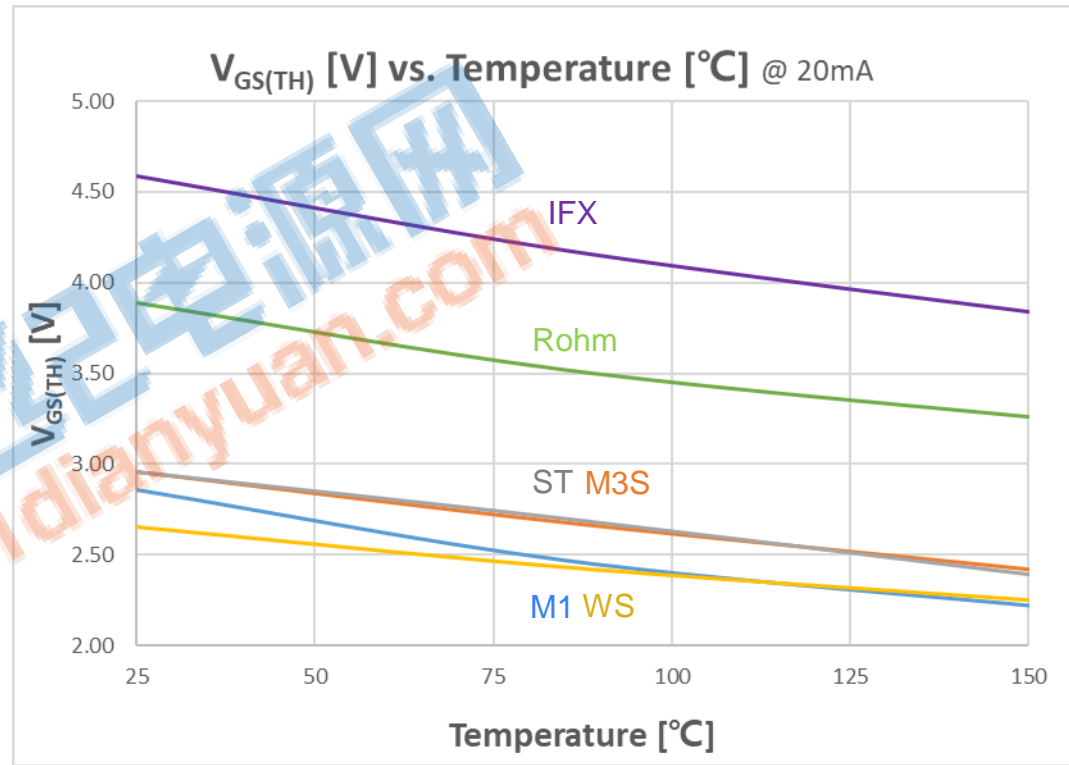
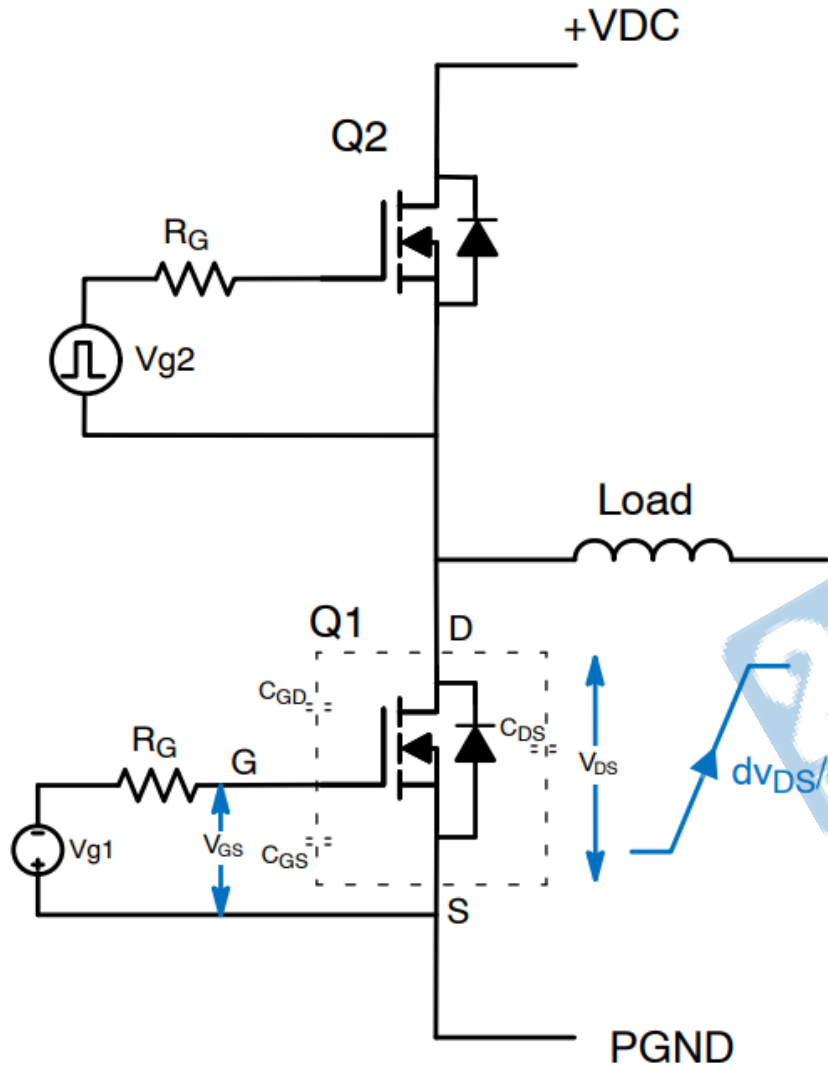
<https://www.onsemi.com/download/application-notes/pdf/and90103-d.pdf>;

[TND6440 - Paralleling SiC MOSFETs Process Impacts and Gate Resistors Setup \(onsemi.com\)](#);

<https://ieeexplore.ieee.org/document/7931077/>;

<https://www.onsemi.com/download/application-notes/pdf/and90255-d.pdf>;

SiC MOSFET开关等效电路



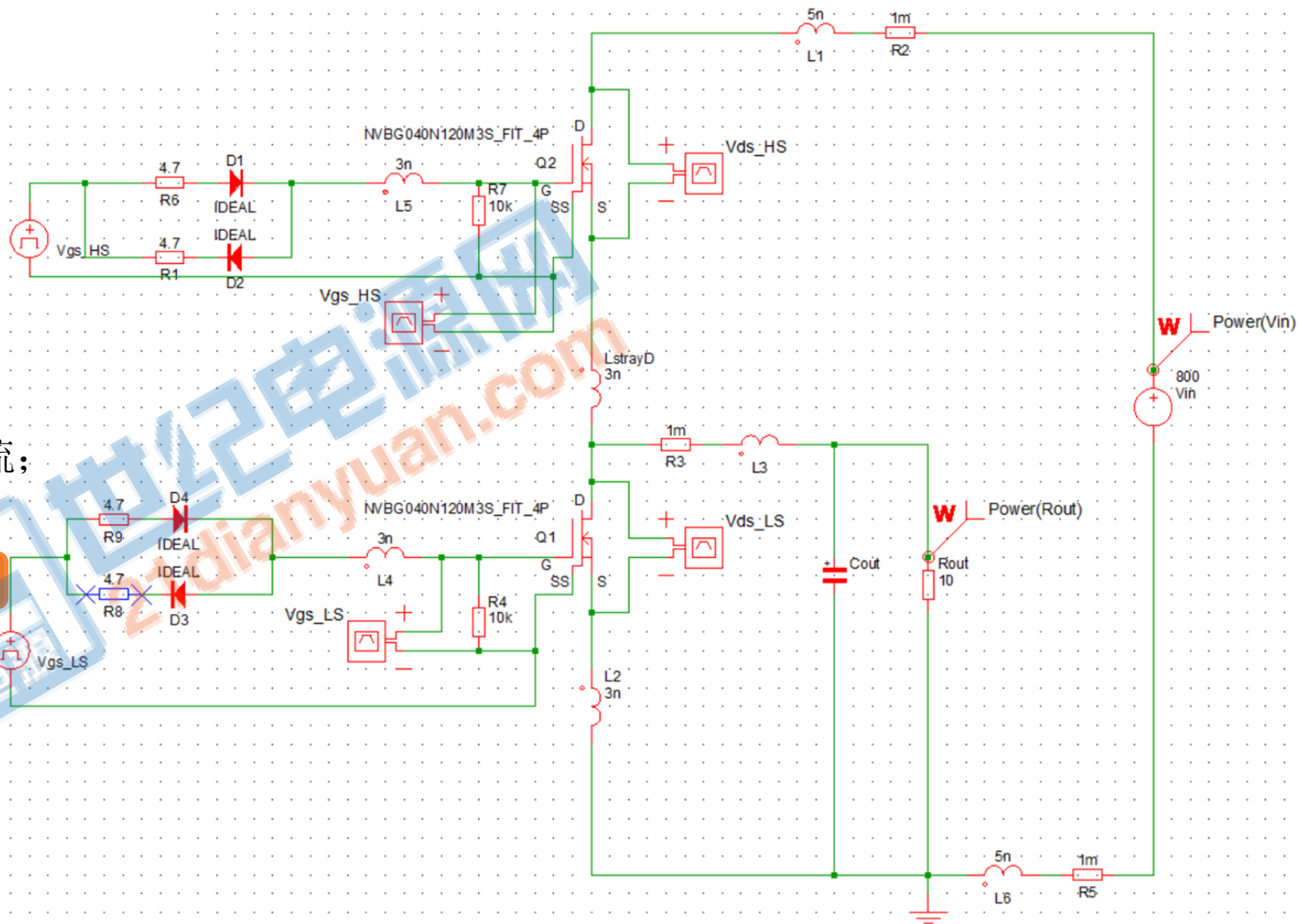
Simetrix仿真电路

测试数据

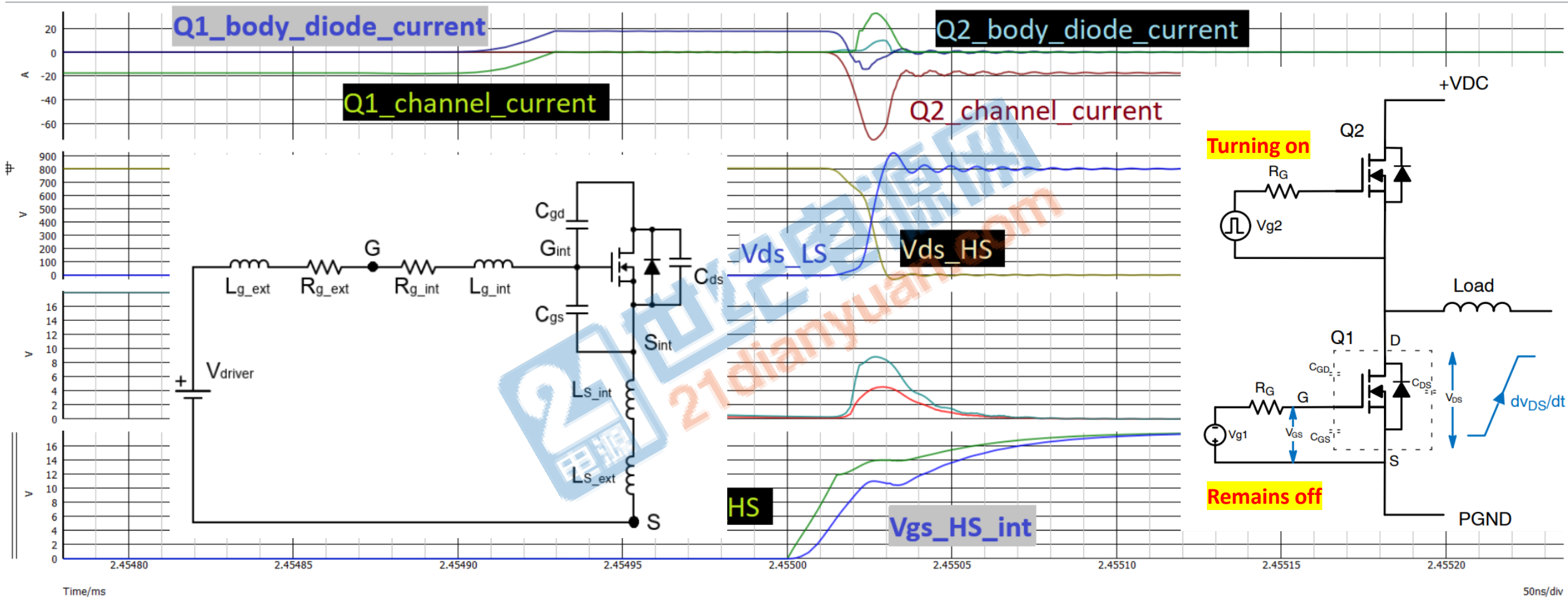
- V_{gs} → 栅源极引脚电压;
- V_{ds} → 漏源极引脚电压;
- V_{gs_int} → 晶圆内部栅源极电压;
- Channel Current → 晶圆导通沟道电流;
- Body diode current → 体二极管晶圆电流;

测试条件

- $V_{in} = 800V$;
- $R_g = 4.7\Omega \sim 25\Omega$;
- $V_{gs_on} = +18V$;
- $V_{gs_off} = 0V, -3V$;
- Load current = $20A \sim 40A$;
- Duty cycle = 48.7%;
- Frequency = 100KHz;

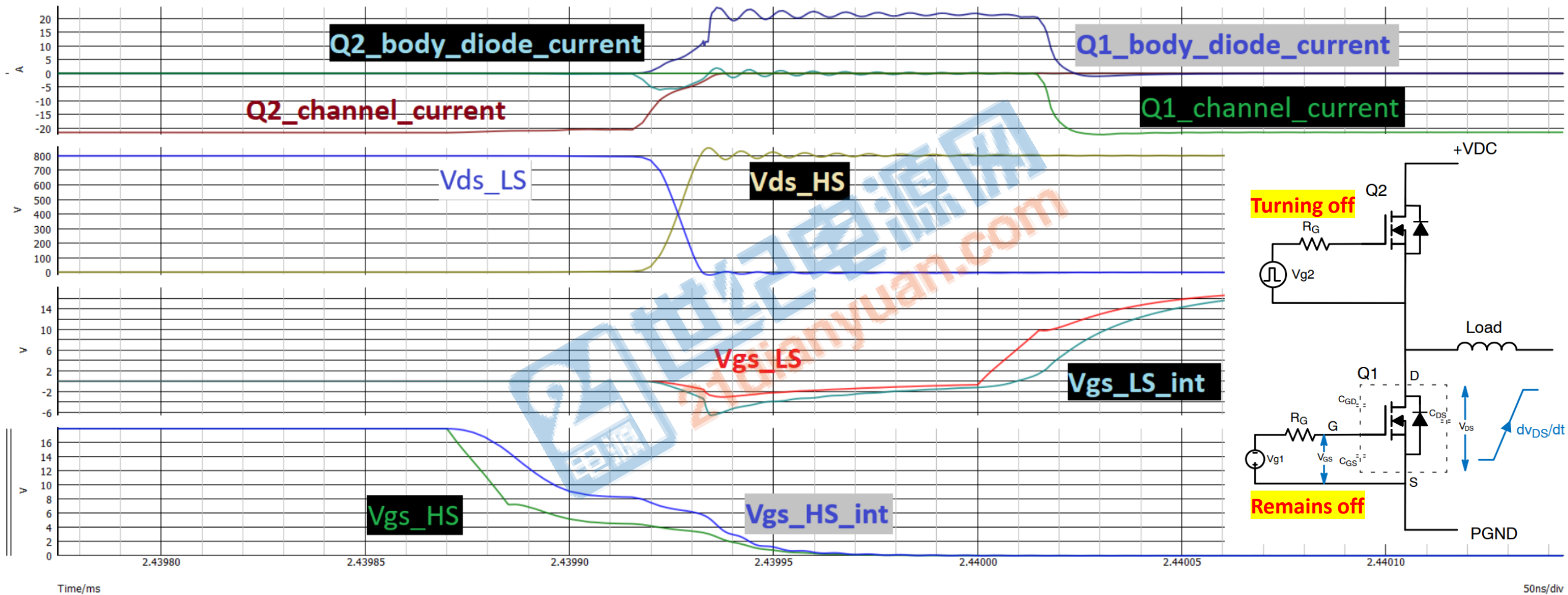


半桥变换器低侧MOSFET的寄生导通问题 $R_g = 4.7 \Omega$



50ns/div

半桥变换器低侧MOSFET的寄生负压尖峰问题 $R_g = 4.7 \Omega$

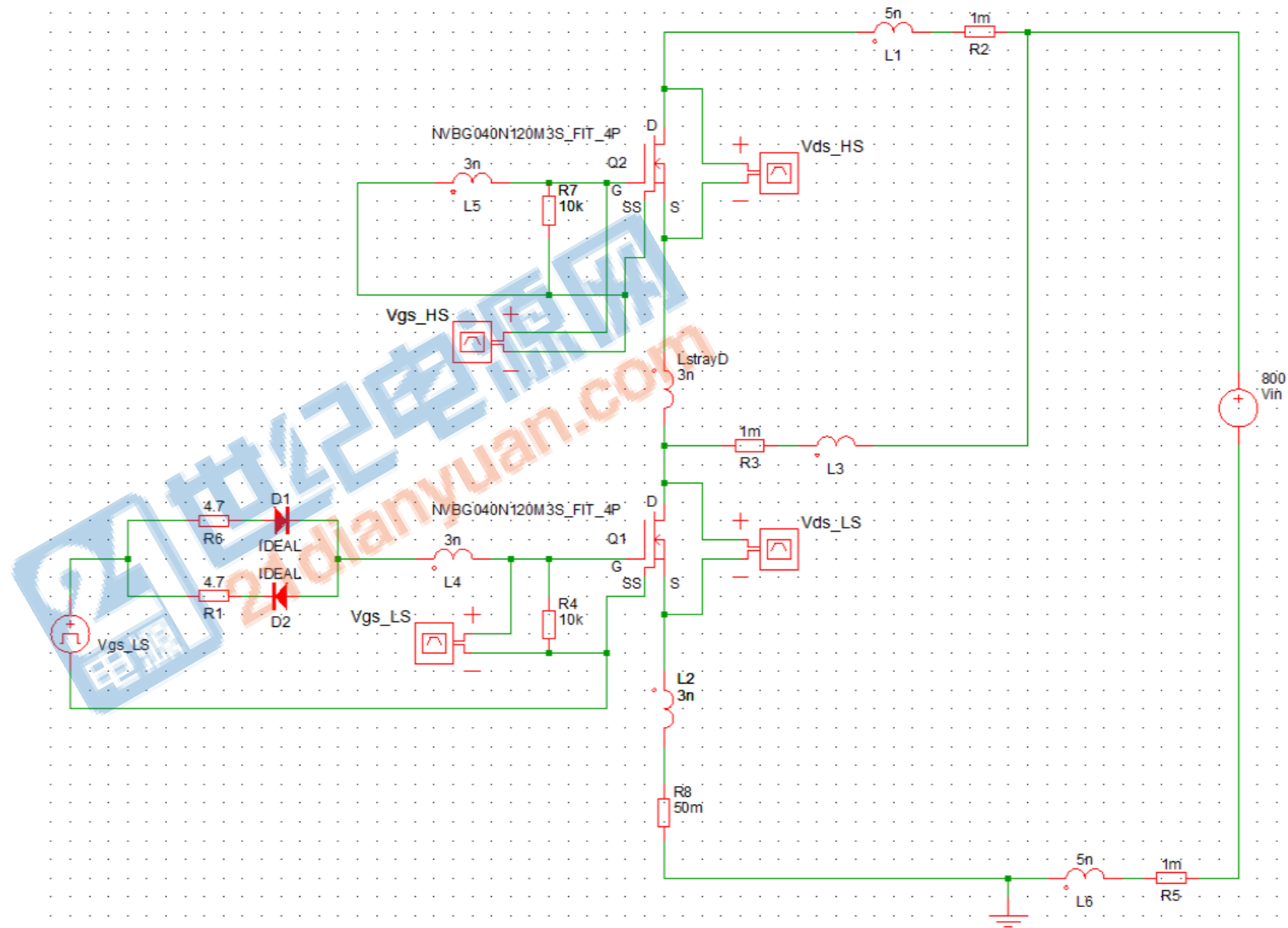


50ns/div

双脉冲测试电路观察PTO寄生误导通现象

测试条件

- $V_{ds} = 800V$;
- CH1: V_{GS_LS} (6 V/div);
- CH2: V_{DS_LS} (300 V/div);
- CH3: V_{DS_HS} (300 V/div);
- CH4: I_D (20 A-40 A/div);
- CH5: V_{GS_HS} (6 V/div);



开关波形 $V_{gs_off} = 0\text{ V}$, $I_D = 40\text{ A}$ $R_{g_on/off} = 4.7/4.7\ \Omega$ 有无米勒钳位对比

$V_{ds} = 800\text{V}$;

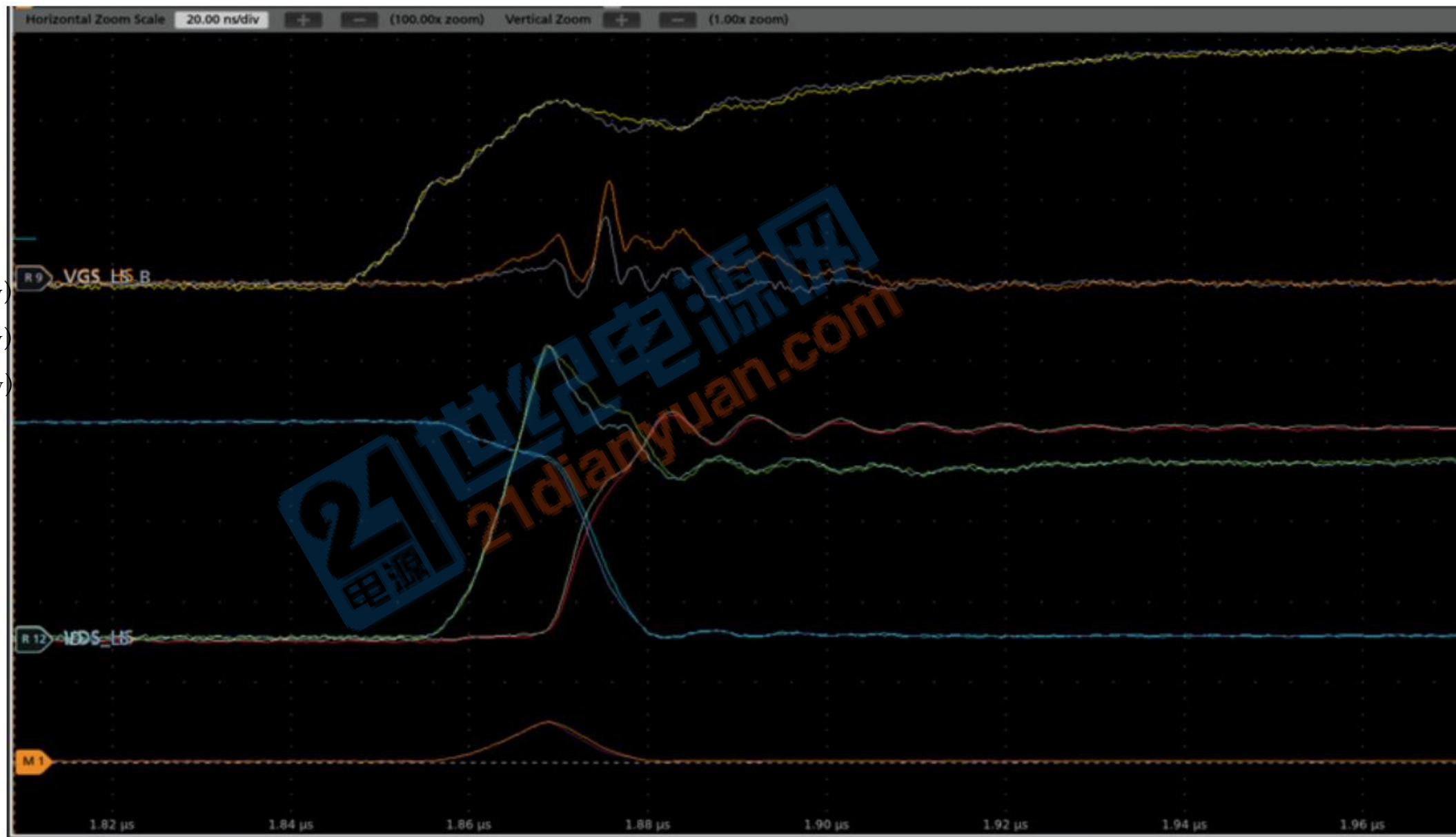
CH1: VGS_LS (6 V/div);

CH2: VDS_LS (300 V/div)

CH3: VSD_HS (300 V/div)

CH4: ID (20 A-40 A/div)

CH5: VGS_HS (6 V/div);



21世纪电源网
21dianyuan.com

开关波形 $V_{gs_off} = 0\text{ V}/-3\text{ V}$, $I_D = 40\text{ A}$ $R_{g_on/off} = 4.7/4.7\ \Omega$ 无米勒钳位

$V_{ds} = 800\text{ V}$;

CH1: VGS_LS (6 V/div);

CH2: VDS_LS (300 V/div);

CH3: VSD_HS (300 V/div);

CH4: ID (20 A-40 A/div);

CH5: VGS_HS (6 V/div);



开关波形 $V_{gs_off} = 0\text{ V}/-3\text{ V}$, $I_D = 40\text{ A}$ $R_{g_on/off} = 4.7/4.7\ \Omega$ 有米勒钳位

$V_{ds} = 800\text{ V}$;

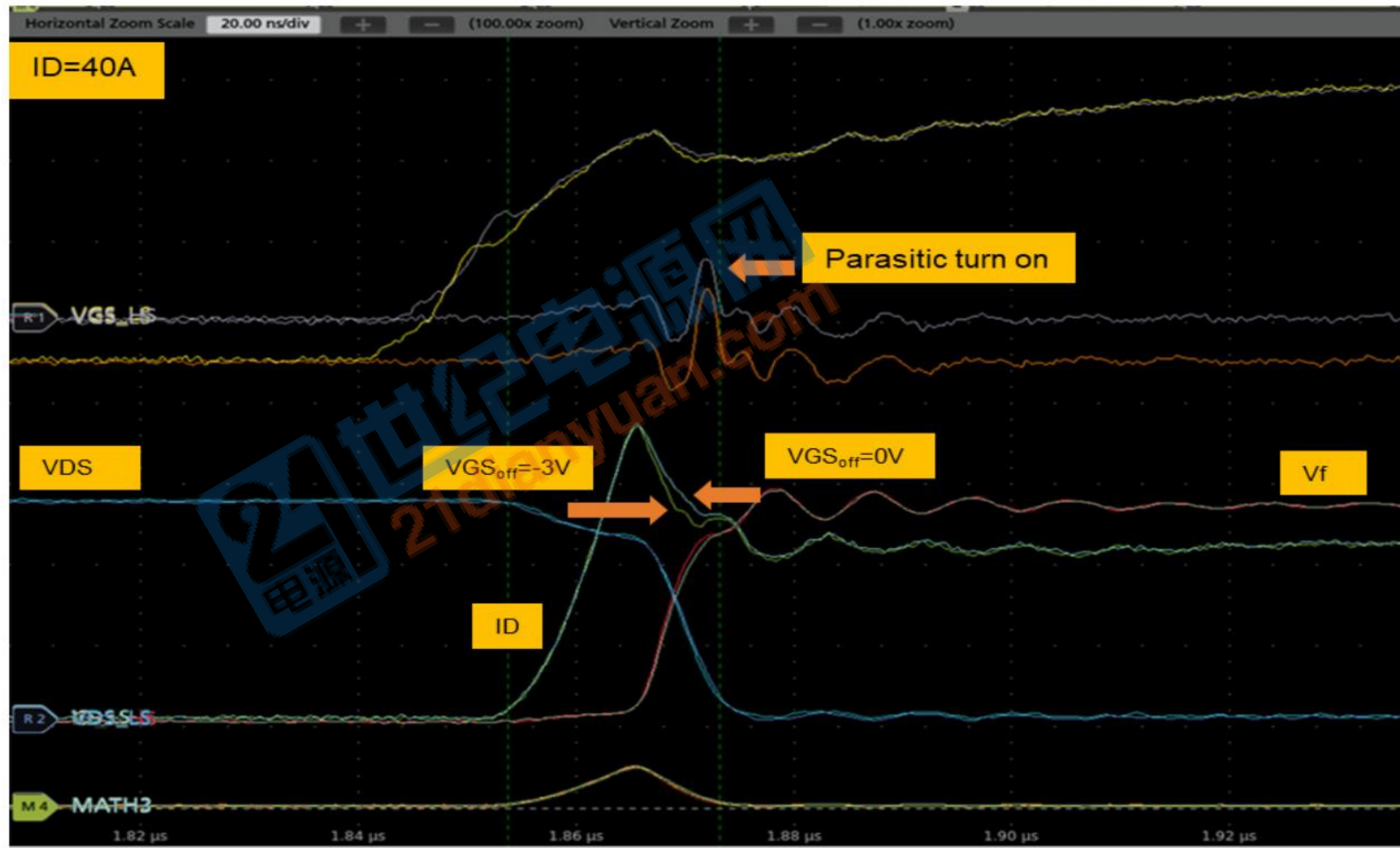
CH1: V_{GS_LS} (6 V/div);

CH2: V_{DS_LS} (300 V/div);

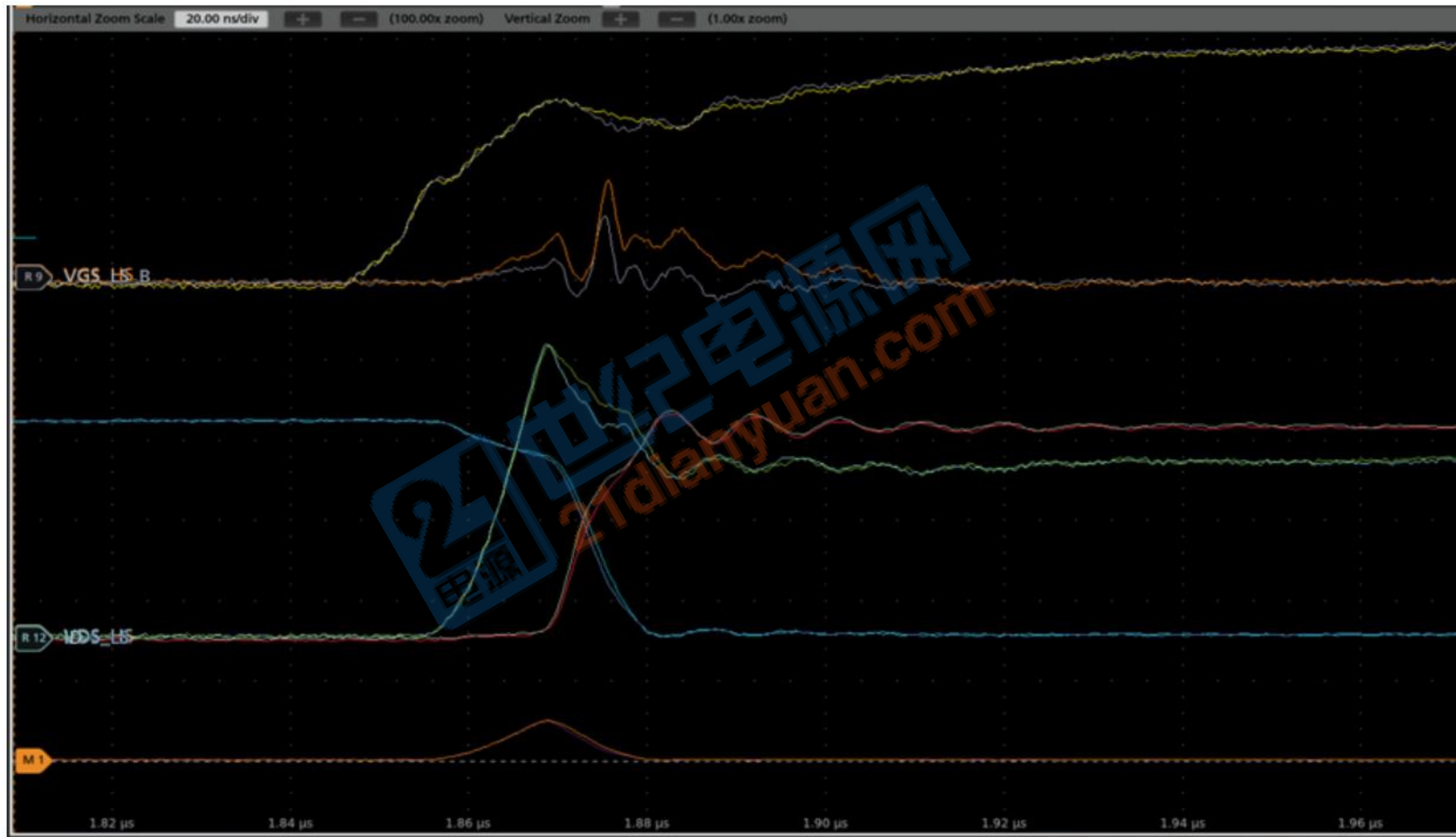
CH3: V_{SD_HS} (300 V/div);

CH4: I_D (20 A-40 A/div);

CH5: V_{GS_HS} (6 V/div);



开关波形 $V_{gs_off} = 0\text{ V}$, $I_D = 40\text{ A}$ $R_{g_on/off} = 10/4.7\ \Omega$ 无米勒钳位



21世纪电源网
21dianyuan.com

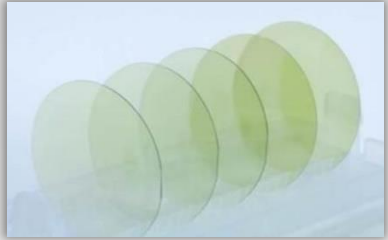
I_D (A)	Rg_on (Ω)	Rg_off (Ω)	Vgs_off (V)	dv/dt Rising (V/ns)	dv/dt Falling (V/ns)	di/dt (A/ns)	Eon (μ J)	Eoff (μ J)
40	4.7	4.7	-3	129	103	7.137	444	146
40	4.7	4.7	0	120	95.74	7.133	456	182
40	10	4.7	-3	89.29	45.82	4.745	611	146
40	10	4.7	0	50	46	4.6	622	182

SiC VS. Si

- 增大Rg_on/Rg_off比值使用0V关断电压同样可以有效减小栅极串扰带来的误导通风险但是会增大开关损耗；
- 使用有米勒钳位功能的隔离驱动结合0V关断电压可以避免牺牲开关速度，而导致的较大开关损耗。

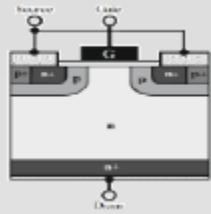
onsemi EliteSiC Leadership: From Substrate to Systems

Substrates / Epi

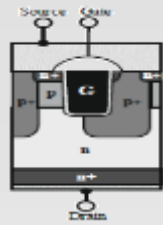


- 150/200mm SiC wafering & epi fully internal in **onsemi** today

Fab



SiC Planar available today



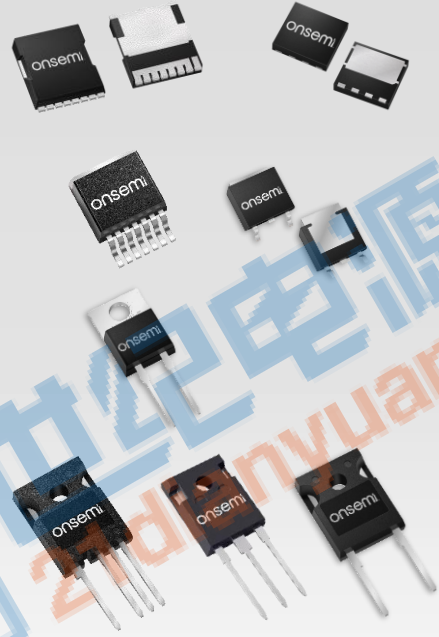
Working on trench for the future



200mm migration ready

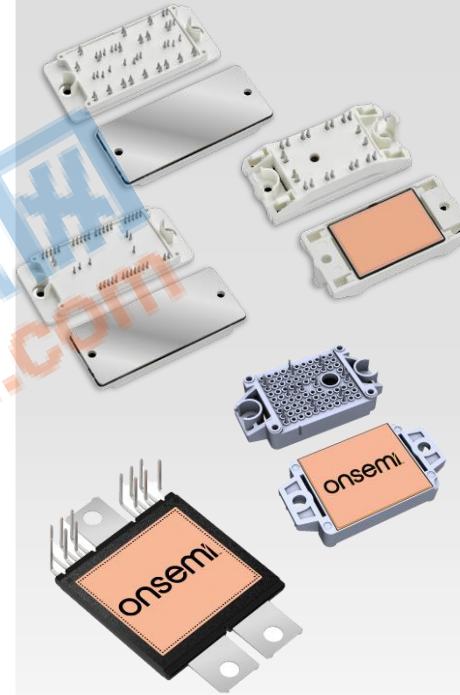
- Fabs ready today for 150mm→200mm migration

Devices / Die



- Full portfolio of diodes & MOSFETs
- Broad base of packages
- Die only & metal options
- Auto & Industrial devices

Modules



















- Case & transfer molded options
- Full portfolio of hybrid & full SiC modules
- Single & dual cooling, direct & indirect














Systems



- Deep application & system know-how for automotive & industrial
- EMEA, US, Asia based apps support

onsemi SiC MOSFET and Diode Families

Family	Series	Optimization	650V	900V	1200V	1700V	Primary Applications
M1	M1	Low RDS(ON) High SCWT			..120SC1	..170M1	     
M2	M2	Low RDS(ON) High SCWT	..065SC1	..090SC1			   
M3	M3S	High speed	..065M3S		..120M3S		  
	M3P, M3e	Low RDS(ON) High SCWT			..120M3x SCWT dependent		  

Family	Optimization	650V	1200V	1700V	Primary Applications
D1	High IFSM	..065A	..120A	..170A	    
D2	Low QC	..065B			  
D3	Low QC x VF		..120C		    

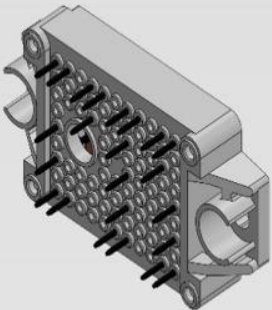


In Development



Gel-filled Modules for Energy Infrastructure

F1



1.2 mm press-fit pins
Solder pins

With TIM/no TIM

Q0



1.2 mm press-fit pins
1.6 mm press-fit pins
Solder pins

With TIM/no TIM

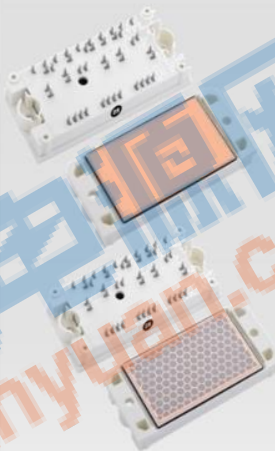
F2



1.2 mm press-fit pins
Solder pins

With TIM/no TIM


Q1



1.2 mm press-fit pins
1.6 mm press-fit pins
Solder pins

With TIM/no TIM

Q2

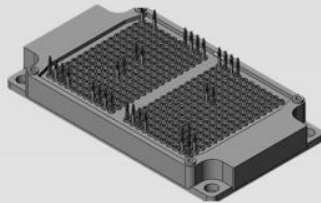


with base plate

1.6 mm press-fit pins
Solder pins

With TIM/no TIM

F5+BP

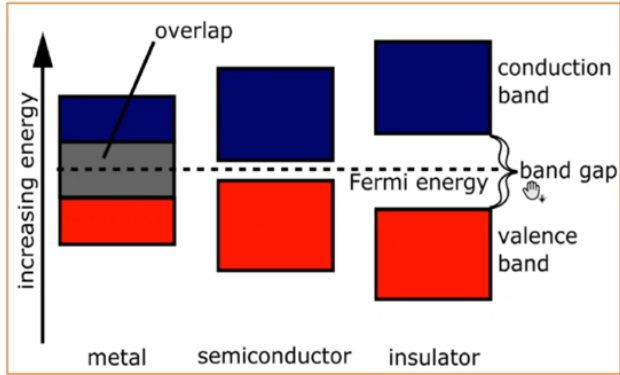


with base plate

1.2 mm press-fit pins
Solder pins

With TIM/no TIM

Key Takeaway !



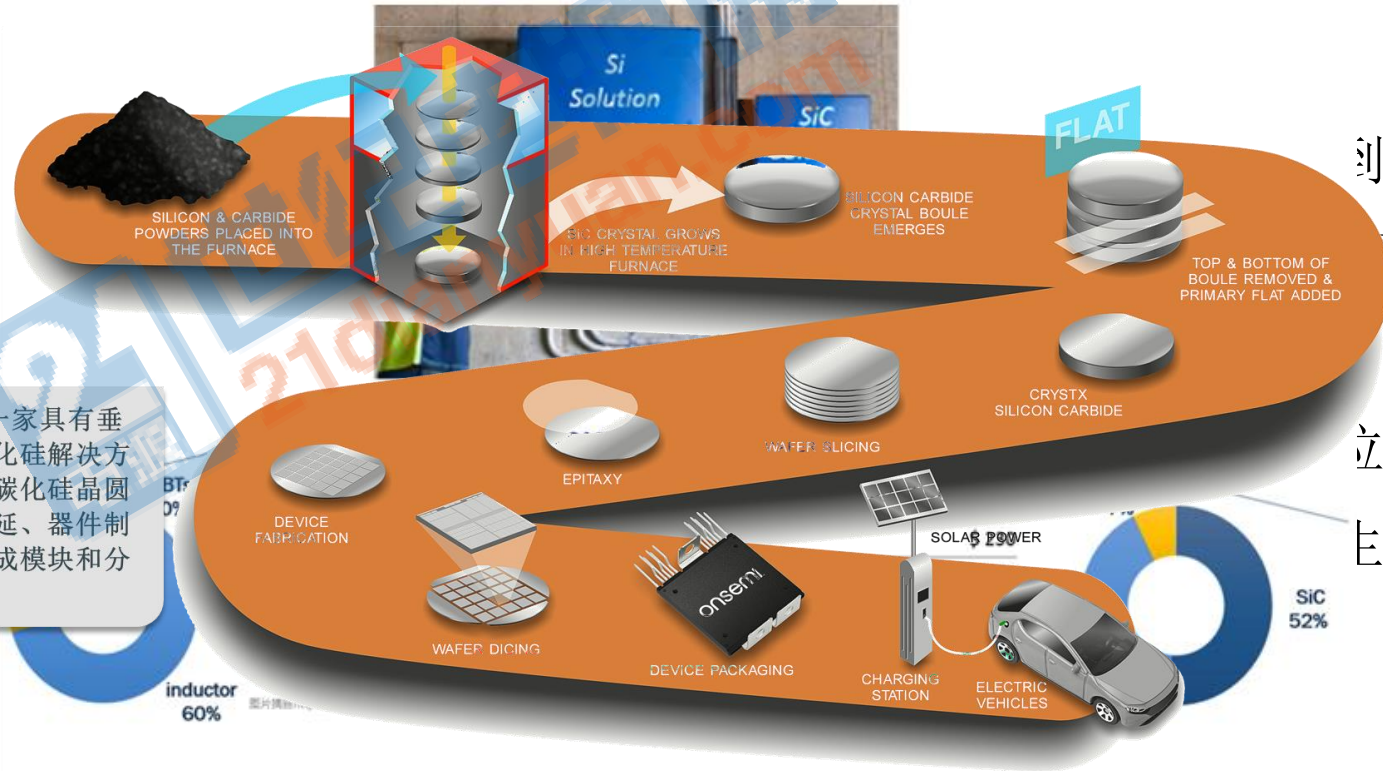
宽禁带 : $E_g > 2.3 \text{ eV}$

- 宽禁带半导体定义：带隙能量 $E_g > 2.3 \text{ eV}$ ；
- 在光伏逆变应用中使用碳化硅方案代替IGBT可以实现更低的BOM成本；

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米



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圖具有高
立功能的
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